RadiationDamagein ChargeCoupledDevices

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DavidRyanSmith

SpaceProjectsandInstrumentationGroup

DepartmentofPhysicsandAstronomy

UniversityofLeicester

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DavidRyanSmith

Abstract

This thesis is concerned with the effects of radiation damag applications. The manufacturing process and operational principles Chapter 2. The space radiation environment, the two radiation dama CCDs, and the effects of radiation on the operational character istics of CCDs are described in Chapter 3.

Chapter 4 presents a study to assess the suitability of novel 1 ow light level L3Vision CCD technology to applications in space. Two L3Vision CCDs were subj ected to proton irradiations representative of doses expected to be received by spacecraft in low Earth orbit. Post-irradiation the devices were found to operate as expected, the effects of r characteristics of the devices being comparable to previous studies.

TheeffectoflowenergyprotonsonCCDsisthesubjectofChapt response to the finding that soft protons could be focused by the m irror modules of the XMM-NewtonspacecraftontotheEPICCCDdetectors.TwoEPIC devices were irradiated with ge than that expected by the Non-Ionising Energy Loss damage relationship, as they deposit most CCD. The observed change in CTI of the EPIC devices on XMM-Newt on is however comparable to the pre-launch prediction, and the component attributable small, <20%.

Chapter 6 presents a study of a specific radiation induced phenomenon, 'Random Telegraph Signals'. Development of analysis software and their radiat ion of two CCDs are discussed before a detailed characterisation of the generated RTS pixels is presented. The study shows that the mechanism behind RTS involves a bi-stable defect linked with the high field regions of a CCD pixel.

Declaration

I hereby declare that no part of this thesis has been previousl y submitted to this or any other university as part of the requirement for a higher degree. The work described herein was conducted solely by the undersigned except for those colleagues and other workers acknowledgedinthetext.

David Ryan Smith

12thSeptember2003

Dedication

Tomy family and every one who believed I could do it.

Acknowledgements

I would like to acknowledge the following people for their help and encouragement over the duration of mythesis work.

Thanks go to my supervisor Andrew Holland for his guidance, advic eand gentle pushing in the right direction, and also to Adam, Richard, Ian, Nick and Alex for the assurance that I was not a 'normal' student.

ThankstoallthestaffoftheSpaceResearchCentrefortheirtechnic alassistanceinandoutofthe labandfortheirgeneralchatandfriendshipthatmademythreeyearssoen joyable.

ThanksalsotothestaffofE2VTechnologies, especially Mark R obbins and Dave Burt, for their wisewords and help when it was needed.

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Chapter1:Introduction

1.1. RadiationDamageinCCDs

The advantages of semiconductor detectors in astronomy have long been recognised. Semiconductorimaging detectors are generally smaller and requi relesspowerthangaseousand solid-state scintillation detectors, demonstrating better signalto-noise, energy resolution and linearityoverawideenergyrange. In the 1960's semiconductort echnologyhadprogressedtoa pointwheremetal-oxide-semiconductor(MOS)devices could be combine dintolargearraysthat allowed the storage and transport of charge through the many e lements of the array. These charge-coupleddevices(CCDs)hadanumberofapplicationsinthee lectronicsworldintheform of memory storage components and analogue signal processors, but it w as the development of siliconCCDsforuseasimagingdevicesinthemid1970'sthat gainedtheinterestofNASA.By 1978NASAhadproducedimagingCCDsof500 ²pixelswithnoiselevelsbelow10electronsand by 1989 devices with 800 ² pixels with improved signal-to-noise and operational reliabilit ywere beingmanufacturedandconsideredforpotentialinstrumentsonupcomingspacemis sions.

The launch of the Galileo mission to Jupiter in 1989 and the Hubble Space Telescope in 1990 resulted in the first astronomical images to be obtained from charge-coupled devices (CCDs) operating in space. The effects of the space radiation environment on CCD operational characteristicswerealsoobservedforthefirsttime. The affectofradiationonCCDimagershad been studied since their initial development, however measureme nts from the devices in space revealed a number of new unexpected effects on device performanc e and output noise. The composition of the space radiation environment is complex and dependent on spacecraftorbitand solar activity. The major limitation to CCD reliability arises from damage caused by the space radiationenvironmentwhichinextremecasescanrenderadevice inoperable. Study of the space radiationenvironmentanditseffectsonCCDshadbegunandisthesubjectofthi sthesis.

CCD detector technology has advanced through the nineties with the development of many techniques to improve the radiation tolerance of devices and capabilities. CCDs have been used as optical and X-ray detector s on a large number of space missions and they emerged as the preferred detectors in all the The current trends in astronomy detector requirements are for pixelsize, increased charge collection efficiency, fasterrea dout and lowernoise. These goals all

lendthemselveswelltothecontinuingdevelopmentofCCDtechnologywithC CDsbeingchosen forseveralfutureopticalandX-rayscientificmissionscurrent lyplannedorunderstudy.

TodatethelargestCCDfocalplaneinstrumentsoperatedins pacearethetwinEuropeanPhoton Imaging Cameras (EPIC) cameras of the X-ray Multi Mir ror (XMM-Newton) spacecraft, each composed of 7 individual CCDs. Focal plane instruments comprised of many more CCDs are envisioned for future missions to fulfil the demand for increased focal plane size. The main astrometric mapper instrument of the GAIA mission is composed of 160CCDscoveringafocal plane area of ~0.5 m², while the wide field imager CCD array planned for the X-r ay Evolving Universe Spectroscopy (XEUS) mission consists of 16 CCDs optim ised for X-ray detection. These missions are scheduled for launchin 2010 and 2015 respectively. The size of t heseplanned instruments necessitates detailed radiation studies of the e nvironment each spacecraft will be locatedinandtheeffectsthatenvironmentwillhaveonthedevices.

The continued use of CCDs in space requires radiation testing of state of the art detectors to deduce their suitability for up coming space applications. There i s also a need to analyse data obtained from CCD detectors currently in orbit to improve understand ing of how the space radiation environment affects device operating characteristics and to characterise specific radiation damage phenomena. Long term measurements of on-orbit device degradation are now available from several spacecraft in different orbits fo r comparison with data obtained from groundbased radiation experiments and modelling.

1.2. ResearchGoals

The work carried out for this thesis is comprised of three aimofthe first study was to assess the potential of using ne technology for space based applications. L3Vision CCDs feature a novel structural design that can reduce the effective readout noise of the device to less than one electron while operating at MHz pixel rates. This attribute is particularly useful fo r low light level ('L3') imaging applications. Two L3Vision CCDs were subjected to represent tive mission doses of protons and the effects of irradiation on the operational characteristics of the device to essert investigated.

The second study examined the effects of low energy proton irradiati on of E2V Technologies CCD22devices. This is the same type of device used in the EPI Cfocal plane in struments of the XMM-Newton spacecraft. The investigation was carried out in respons eto the discovery that soft

protons could be focused by scattering interactions with the mirro rs of the Chandra (formerly AXAF) satellite onto the focal plane of the AXAF CCD Imagi ng Spectrometer (ACIS) instrument. The XMM-Newton spacecrafthas a similar mirror stru cture to Chandra and is subject to the same focusing problem. A critical need for characteris at ion of the possible damage caused by different soft proton fluences was addressed with this work both experimentally and theoretically with the development of a computational model by the author.

The third radiation study involved the in-depth study of a particular radiation induced phenomenon in CCDs, fluctuating bright pixels, or 'Random Telegraph S ignals' (RTS). RTS pixels have been observed in many CCD types as a result of i rradiation and the underlying mechanism is not well understood. A detailed study of the phenomenon in two E2V Technologies CCD47-20 devices was carried out to obtain a better understanding of the characteristics of RTS pixels and to improve on the current acc epted model of the underlying mechanism.

The work carried out for this thesis was funded by a Co-operati ve Award in Science and Engineering (CASE) studentship from the Particle Physics and A stronomy Research Council (PPARC) in collaboration with E2V Technologies (formerly Mar coni, formerly EEV) of Chelmsford, Essex, England.

1.3. ThesisOrganisation

The rehave been an umber of these son different aspects of CCD studies production of the contraction of thedbythegroupat the University of Leicester including an investigation of the feasibility of detecting X-rays with conventional video CCDs (Lumb 1983), the use of high resistivity sili con in CCDs to improve on damage effects in CCDs forhighenergyX-raydetectionefficiency(Chowanietz1986),radiati space applications (Holland 1990), the soft X-ray response of CCDs (Castelli 1991), three-dimensional model ling of a stronomical CCDs for X-ray and UV detection(Kim1995),fine structureeffectsinCCDsdevelopedfortheJET-Xinstrument (Keay 1997), device modelling of CCDs for the CUBIC mission (Hutchinson 1999), the use of CCDs fo rX-ray polarimetry (Hill 1999) and the use of CCDs for exotic atom X-ray spectroscopy to de termine the charged pion massandmuonneutrinomassupperlimit(Nelms2002).

TheworkinthisthesiscontinuestheCCDthemewithafurther investigationofradiationdamage effectsinCCDs,inparticulartheeffectsofprotonirradiationon noveldevicesforlowlightlevel

applications, the effects of low energy protons on the EPICMOS CCDs of XMM-Newton and the underlying mechanism behind radiation induced fluctuating CCD pixels.

The thesis is organised into seven chapters including this int roduction. Chapter 2 describes how CCDs are manufactured, the structure of the different types of device available, how CCDs store and transport charge, CCD noise sources and how a CCD detects pho tons. A number of terms used for describing a CCD's performance are also detailed.

Chapter 3 outlines the space radiation environment and its effec ts on CCD operational characteristics. The various components of the space radiation environment are discussed before the two important radiation damage mechanisms for the study of r adiation damage in CCDs, ionisation and displacement damage, are described.

Chapter4isaninvestigationoftheeffectsofprotonirradiat ionofL3VisionCCDstodeducethe suitability of this novel device technology for space applica tions. The device structure is described, followed by a description of the protonirradiation experim ents and the effect proton irradiation hadon the operational characteristics of the devices.

Chapter 5 describes soft protonir radiation experiments carrie edout on CCD 22 devices, the same as those of the European Photon Imaging Cameras of XMM-Newton, to assess the effects of different lowener gyproton fluences on the device operating charace teristics. The development of a computational model to simulate the charge transfer efficiency ychanges resulting from the soft protonir radiations is also presented.

Chapter 6 first describes an initial study of the 'Random Telegr aph Signal' phenomenon in a CCD47-20 device. This study was carried out to allow improvement of the experimental setup and the development of analysis software for a farmore in-dept hstudy of the phenomenon using a second CCD47-20 device. The detailed study is then presented, afte r which the proposed theoretical models for explaining the mechanism behind RTS are discussed.

The final chapter, Chapter 7, recounts the main conclusions of this sthesis and assesses the possible directions for future work.

1.4. Publications

Some of the results in this thesis are contained within the following publications. The thesis chapters to which these papers refere regiven in brackets:

- **Smith,D.R.**, A.D.Holland,M.S.Robbins, "TheeffectofprotonsonE2VTechnologies L3VisionCCDs", *Nuc.Inst.andMeth.*, vol. **A513**,(2003),pp.296-99[Chapter4].
- Abbey, A.F., R.M. Ambrosi, **D.R. Smith**, E. Kendziorra, I. Hutchinson, A. Short, P. Bennie, A. Holland, T. Clauss, M. Kuster, W. Rochow, M. Brandt, M. J. L. Turner, A. Wells, "The effect of lowener gyprotons on the operational characteristics of EPIC -MOSCCDs", *Proc. RADECS*, (2001) [Chapter 5].
- Ambrosi,R.M., **D.R.Smith**, A.F.Abbey,I.B.Hutchinson,E.Kendziorra,A.Short, A.Holland,M.J.L.Turner,A.Wells,"Theimpactoflowenergyprotondamageont he operationalcharacteristicsofEPIC-MOSCCDs", *Nuc.Inst.andMeth.*, vol. **B207**,(2003), pp.175-85[Chapter5].
- Ambrosi, R.M., A.D.T. Short, A.F. Abbey, A.A. Wells, **D.R. Smith**, "The effect of proton damage on the X-ray spectral response of MOSCCDs for the Swift X-ray Telescope", *Nuc. Inst. and Meth.*, vol. **A482**, (2002), pp. 644-52 [Chapter 5].
- **Smith,D.R.**, A.D.Holland,M.S.Robbins,R.M.Ambrosi,I.B.Hutchinson,"Protoninduced leakagecurrentinCCDs", *Proc.SPIE*, vol. **4851**,(2003),pp.842-48[Chapter6].
- **Smith,D.R.**, A.D.Holland,I.B.Hutchinson, "Randomtelegraphsignalsinchargecoupled devices", accepted for publication in *Nuc.Inst.andMeth.*, vol. **A**,(2003) [Chapter 6].
- **Smith,D.R.** ,R.M.Ambrosi,A.D.Holland,I.B.Hutchinson,A.Wells,"Thepromptparticle backgroundandmicrometeoroidenvironmentatL2anditsimplicationsforEdding ton",in press, *Proc.2* nd *EddingtonWorkshop* ,ESASP-485,(2003)[Chapter6].

Chapter2:TheChargeCoupledDevice

This chapter describes how CCDs are manufactured and the underly ing principles of CCD operation. Charge storage, transfer and readout are detailed for both surface channel and buried channel devices. The various components of CCD noise are then discus sed followed by the definition of several terms used to describe a CCD soperational characteristics.

2.1. Introduction

The charge-coupled device (CCD) was originally conceived by Boyle and Smith (1970) at Bell Telephone Laboratories in the late 1960's, and consists of a meta 1-oxide semiconductor (MOS) capacitor array usually made of silicon. An electrode structure i s fabricated over the surface of thedevicethatallowsdepletionregionstobeformedunderbiasedele ctrodes.Chargeiscollected in these depletion regions and by changing the bias of subsequent electrodes of the device, the charge 'packet' is transferred to an output circuit where the level of charge is measured. The technique of transferring, or 'coupling', charge from one electrod e to another has a number of applications, for example analogue signal processing, high density me mories and most importantly, imaging devices (Barbe 1975). For use as imaging de vices, higher quality fabrication methods need to be employed to produce CCDs with fewer structural defects (Jastrzebski et al. 1981). Such defects are not as important in signal processing and memory devices where higher charge signals are used. In a CCD imagi ng device, charge is generated in proportion to the incident light intensity by the process of ionisa tion. The signal charge is collected in the depletion region of the MOS capacitors before itistransferredtotheoutputnode, amplified and measured. The distribution of the collected charge intheCCDformsanelectronic image which is reconstructed after readout of the device. Sinc e the initial design of the CCD manyimprovementsinfabricationmethodsanddevicestructureha vebeeninstigatedtoproduce modern devices that can be used for high resolution imaging and spectr oscopyintheX-ray and optical wavebands while with standing the rigours of being launched i nto space and subjected to the spacera diation environment for the duration of their operation.

Thischapterdescribeshow CCDs are fabricated and how a CCDc ollects, transfers and reads out charge. The different noise sources are also described along wit had is cussion of the performance parameters that characterise a device. Further information a bout CCDs and their applications can be found in Beynon and Lamb (1980), Sze (1981), Howes and Morgan (1979) and Jane sick (2001).

2.2. CCDFabricationandStructure

A CCD consists of strips of polysilicon electrode formed into orthogonal 'channelstops' that prevent charges preading along the CCD pixel consists of a set of two to four electrodes, usually charge and are used to 'clock' the signal packet to the reado uphase' devices are the most common due to their high process tolera two and four phase devices are also available. Charge collecte the biased electrodes and channels tops is stored under an oxide instance the device. Such a device is called a 'surface channel' CCD. Fig phase surface channel CCD.

an array by the presence of eller engthoftheelectrodes. Each three, that when biased collect utnode of the device. These 'three a nceandhighyield, although dinthe potential wells formed by ulating layer at the surface of ure 2.1 shows a section of a three

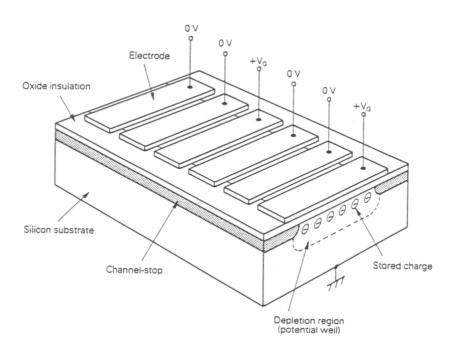


Figure 2.1 A section of a surface channel CCD showing the electrodes, channel stops, charge storagearea and different layers of the CCD

The idea of transferring charge in a 'buried channel' was fir st suggested by Boyle and Smith in 1970, with the first test structures produced by 1972 (Walden et al. 1972) . The buried channel devices to resand transports charge a short distance, ~ 0.5 µm, below the Si-SiO 2 interface, greatly reducing the signal loss to lattice defects in the interface region. Impurity atoms in the silicon lattice have associated discrete energy levels that li ebet ween the conduction and valence bands and it is here that the carriers can be come 'trapped' (Grove 1967). Figure 2.2 illustrates the main

defect complexes found in CCDs and lists some of their properties. L not only during the CCD manufacturing process but are also created damage by energetic particles. Displacement damage is discussed in mor

atticedefects are produced as a result of displacement edetail in Chapter 3.

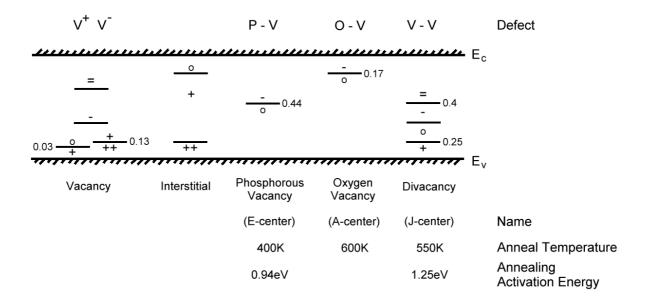


Figure 2.2 Adiagram of the main defect complexes that form as a result of displacement damage in CCDs. Details of the energy levels induced in the silic on band-gap and the approximate annealing temperatures and activation energies are given. The energy levels are in eV measured from the nearest banded ge

The CCD fabrication process involves firstly growing p-type epi taxial silicon over a heavily dopedp+-typesiliconsubstrate. The use of a heavily doped substrate has theadvantageoverbulk silicon that intrinsic gettering occurs during processing, whe re defects in the epitaxial silicon migrate to the substrate, increasing the purity and uniformity of the epitaxial layer and leaving fewer cosmetic defects in the finished device. The image ar ea of the CCD is then defined by borondopingofthenon-imagingareaformingap+peripheralregion.Charg efromtheseareasis of the CCD, therefore not sweptaway by contacts to an external power supply during operation contributing charge to the image. The silicon surface is cove red in a thermally grown oxide

creating an insulating layer between the silicon and the polysili conelectrode structures that will be placed on top. The buried channel is then created by ion implantation, u sually phosphorous, ×10 ¹⁷cm ⁻³, creating ap-n junction with the throughtheoxidelayertoapeakconcentrationof~5 underlying p-type silicon. A silicon-nitride layer is then added to prevent contamination of the underlying silicon during later manufacturing steps, prevent further non-uniform growth of the $^{\circ}C$ oxide layer and improve the integrity of the electrical insula tion of the two layers. A 1000 anneal is then given to anneal displacement damage resulting f rom the ion implantation. Photolithography processes are then used to build up the polysilic on ele ctrodestructuresontop ofthesilicon-nitride. Each electrode is deposited in turnwi th0.2 µmto0.3 µmofoxidebetween each one, before a final layer of vapour phase grown oxide, 'VAPOX' , is added to protect the electrode structure from particle contamination. Contact holes a re then opened up in the oxide where bond pads and tracks to the electrodes and output register are needed and each device is cut from the wafer to be wire bonded and packaged for use. A more detailed description of the CCD manufacturing process is given in Morgan and Board (1983). A cros s-section through a surface channel CCD is shown in Figure 2.3 and a buried channel CCD cross-sectionisshownin Figure 2.4. The electrodestructure and various layers within each devic earelabelled.

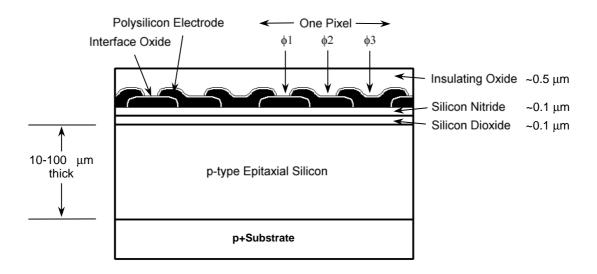


Figure 2.3 Across-section through a surface channel CCD showing the 'overlapping' polys electrode structure ilicon

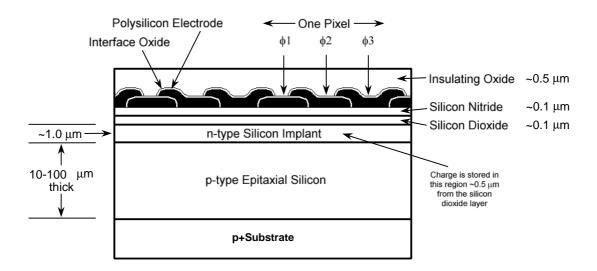


Figure 2.4 Across-section through a buried channel CCD showing the chargestor ageregion that located away from the Si-SiO 2 interface

The structure of a completed CCD is shown in Figure 2.5. The devic eshownisa'frametransfer' device which has an 'image' section and a 'store' section. A d evice without a store section is called a 'full frame' device. During readout of the collecte d charge, additional charge will be accumulated if the image section of the CCD remains exposed to light. Onemethodofpreventing thisextrachargecausingunwantedimagesmearduringreadoutistoha veashutterthatcanclose over the image section, while another more commonly used technique is the use of a frame transfer device with a shielded store section. In the fram e transfer device the image charge is readoutcanoccurwithnoadditional transferred quickly to the store section of the device wherechargebeing accumulated. This type of device also has the added advantageofallowingthenext imagetobetakenwhilereadoutistakingplace.

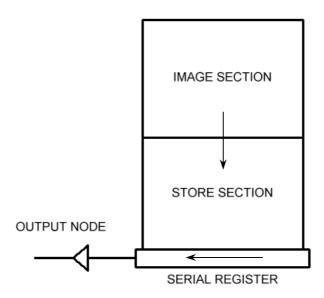


Figure 2.5 A schematic of a 'frame transfer' CCD. The arrows indicate the charge transfer direction

2.3. PotentialsinaCCD

2.3.1. The Surface Channel Device

Signal charge generated by incident photons is collected in the 'depletion' region under the biased electrode in each CCD pixel. The potential applied to an e lectrode repels the majority carriers forming the depletion region. It is useful to consider a single MOS capacitor to understand the potentials and electric field in a CCD. Figure 2 .6 shows the effect of electrode ermilevel, E_F , is biasontheenergybandsoftheunderlyingsilicon. WithnoappliedvoltagetheF the same in the semiconductor and the metal. When a voltage i s applied to the electrode the potential drops across the junction. Band bending occurs in the semi conductor as the E_F level stays flat as no current flows. If the bias voltage is made more negative the valence band bends nearer to E_F resulting in an increased concentration of majority carriers , holes in the case of p-typesilicon, developing near the Si-SiO 2 interface. This situation is called 'accumulation'. For small positive bias the valance band bends away from E_F creating a region depleted of majority charge carriers. The depth of this region into the silicon inc reases as the applied voltage is increased. This situation is called 'depletion'. For large positi ve bias the intrinsic level bends

below E_F and minority carriers accumulate at the interface while majority carriers are removed by a substrate connection. This situation is therefore called 'inversion'. If the bias is increased further to the point where the conduction band crosses E_F , 'strong inversion', the number of majority carriers at the surface becomes very high. The bulk siliconis shielded from the applied bias and no further increase in the depletion depth can be made.

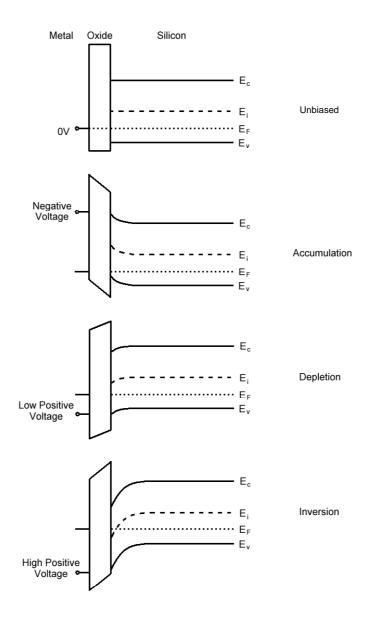


Figure 2.6 The effect of electrode bias on the energy bands of the underlying sili

The potential profile in the depletion region of a uniformly doped p-type silic on C Disrelated to the dopant concentration, N_A , by Poisson's equation:

$$\frac{d^2V}{dx^2} = \frac{qN_A}{\varepsilon_{Si}\varepsilon_0} \tag{2.1}$$

Where q is the electronic charge, \mathcal{E}_{Si} is the relative permittivity of silicon and \mathcal{E}_0 is the relative permittivity of free space. Integrating equation 2.1 with the boundary condition that the electric field is zero at the depletion depth D, gives a linear expression for the electric field into the device:

$$\frac{dV}{dx} = \frac{qN_A}{\varepsilon_{Si}\varepsilon_0}(x - D) \tag{2.2}$$

Integrating equation 2.2 with respect to x gives an expression for how the potential changes with distance, x, into the silicon:

$$V = \frac{qN_A}{2\varepsilon_{Si}\varepsilon_0}(x-D)^2 \tag{2.3}$$

At the silicon surface $V = V_S$ and x = 0, giving an expression for the relationship between the depletion depth and the surface potential:

$$V_S = \frac{qN_A D^2}{2\varepsilon_{Si}\varepsilon_0} \tag{2.4}$$

Therefore:

$$D = \sqrt{\frac{2\varepsilon_{Si}\varepsilon_{0}V_{S}}{qN_{A}}}$$
 (2.5)

Figure 2.7 shows the potential profile of a surface channel deviage with a 0.2 μ moxide layer on silicon with a dopant concentration of 1 \times 10 15 cm $^{-3}$ with 10 V applied to the gate electrode (Holland 1990). Figure 2.8 shows the potential profile under two electrodes of a surface channel

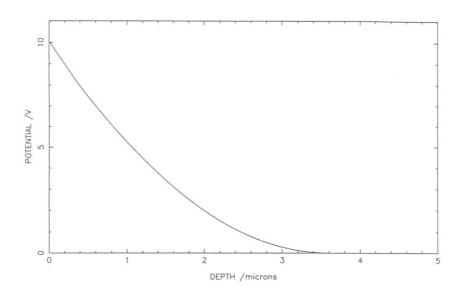


Figure 2.7 The potential profile of a surface channel device

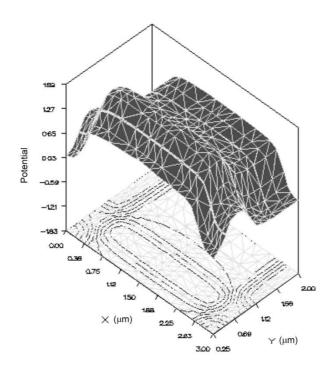


Figure 2.8 The potential profile under two CCD electrodes in a surface cha biased, one unbiased, modelled using the EVEREST Device Modelling S GenerationEvents(Fowleretal.1998)

nnel device, one oftware for Charge

2.3.2. TheBuriedChannelDevice

In the buried channel CCD, when a potential is applied to the n lay er a depletion region is formed. The depletion layer at the p-n junction between the n-type bur ied channel implant and the p-type underlying epitaxial silicon, grows as the applied elec trode voltage is increased. A point arises where the depletion layers meet and any further bia s on the n layer has no further influence on the potential profile. This condition is called 'pinch-of f' and results in the creation ofapotentialmaximum~0.5 umbelowtheSi-SiO 2interface.Anyincreaseinelectrodebiaswill increase the depth of the depletion region into the silicon but the po tential minimum remains in the same place. Solving Poisson's equation numerically for diff erent applied bias produces the plotinFigure 2.9. The solid and dashed lines represent the potential pr ofileunderelectrodesheld underanintersectionof at 10 V and 0 V respectively, the dotted line showing the potential profile boththechannelstopandthe10Velectrodeandthep+-typeisolationcolumns(Holla nd1990).

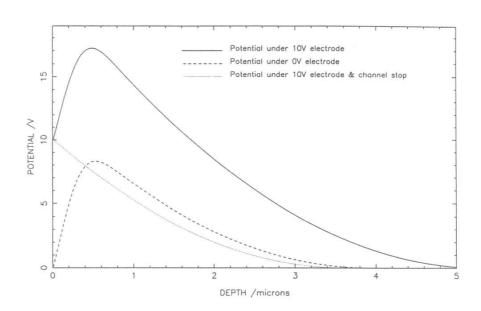


Figure 2.9 The potential profile of a buried channel device

2.4. ChargeTransfer

Charge collected under the bias electrode of each pixel in the columns of the device by a series of 'clocking' pulses. This transfer and is brought about by sequencing the bias of the electr results in all the charge packets moving down one row, the firs tp register which has one bias electrode held high to preserve Figure 2.10 shows a clocking sequence transferring charge from under In the initial stages of transfer, the charge is moved by se If induce charge distribution concentration gradient. Once the charge distribution the fringing-field between the electrodes becomes the dominant in (Hsiehand Luk 1984). A final factor influencing the flow of charge have an effect in low field regions (Banghart et al. 1991).

CCD is first moved down the transfer is known as 'parallel' odes in each pixel. One cycle tpacket moving into the readout we the horizontal information. nunder one electrode to another. If induced drift brought about by the stri bution becomes more uniform the fluence on charge movement eisthermal diffusion that may

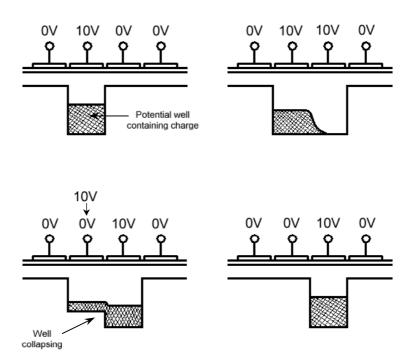


Figure 2.10 The charge transfer process

2.4.1. ChargeTransferEfficiency

For scientific imaging CCDs it is important to have good Char reductioninCTEiscausedbyinsufficienttransfertime and bytr apping of charge that is released into following signal packets. The effect of bad CTE is seen as smearing of the source sina CCD image in the direction of charge from the source pixel leading to a spectral lines. When describing the transfer efficiency of a device numerically, it is useful to talk about Charge Transfer Inefficiency, CTI, which is the fraction o for the observed for the source pixel leading to a spectral lines. When describing the transfer efficiency of a device numerically, it is useful to talk about Charge Transfer Inefficiency, CTI, which is the fraction o for the observed for the observed spectral lines.

$$CTI = 1 - CTE \tag{2.6}$$

Givensuitablechargetransfertime, CTI is dependent on the trapping and release time constants of electrons and holes from the trapping sites, governed by Shockley-R and Reed 1952). In a buried channel device with a charge packet resi ding in the n layer, hole capture can be omitted. The traps below mid-band are always occupi ed due to long electron emission time constants and the traps above mid-band have long hole mission time constants. For these reasons only the traps above mid-band are of interes twhere electron capture and emission is dominant. Electron capture and emission is dominant. Electron capture and emission is dominant.

$$\frac{dN_{trapped}}{dt} = \sigma_n v_{th} n_e \left(N_t - N_{trapped} \right) - \sigma_n v_{th} N_c N_{trapped} \exp \frac{-E}{kT}$$
 (2.7)
$$\text{capture} \qquad \text{emission}$$

Where $N_{trapped}$ is the number of trapped electrons at an energy level E below the conduction band edge, σ_n is the electron capture cross-section, v_{th} is the electron thermal velocity, n_{e} is the density of electrons in the conduction band, N_{t} is the density of traps, N_{c} is the density of states in the conduction band, k is the Boltzmann constant and k is the temperature. The electron capture and emission time constants are therefore given by:

$$\tau_{capture} = \frac{1}{\sigma_n v_{th} n_e} \qquad \tau_{emission} = \frac{\exp\left(\frac{E}{kT}\right)}{\sigma_n v_{th} N_c}$$
 (2.8)

The electron capture time constant is dominated by the electron capture cross-section, while the emission time constant is dominated by the trapener gylevel and temperature. In a steady state, the fraction of traps filled, Γ , in a time, Δt , is given by (Bond 1996):

$$\Gamma = \frac{1}{\left(1 + \frac{\tau_{capture}}{\tau_{emission}}\right)} \left[1 - \exp\left(\frac{-\Delta t}{\tau_{capture}}\right) \exp\left(\frac{-\Delta t}{\tau_{emission}}\right)\right]$$
(2.9)

Theelectrontrappingtimeis~10-100nswhilethereleasetim eisdependentonthetrapspecies and can be of order a few 10's of nanoseconds to seconds. If the rele ase time is slow in comparison to the pixel transfer time, charge smearing will be seen in the CCD image. Figure 2.11showstheeffect of CTE on the signal charge packet.

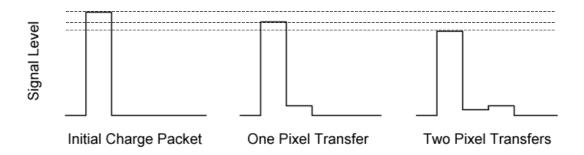


Figure 2.11 The effect of CTE on a charge packet. Signal charge is los tfrom the initial charge packet during transfer and is emitted into subsequent pixels

2.5. ChargeReadout

Aftertransferofa CCD rowinto the orthogonal serial readout egister, each charge packet in the row is clocked onto an output node for amplification and readout. The end of the serial register and the output circuit are shown in Figure 2.12. A number of methods of method employed by the CCD sused for the work in this the sis is as follows:

The reset FET is turned on allowing the output FET to be set t reset FET is then turned off while the bias on the last elect gate, is lowered allowing the charge packet to pass to the outpuntype silicon and biased to form a deep potential well for col signal charge is transferred to the output node, the voltage proportion to the number of electrons in the charge packet, if t its linear region. This relationship is given by:

oareference voltage level. The ectrode in the serial register, the output sput to node. The output node is of lecting the signal charge. As the of the output FET, V_{FET} , changes in he output transistor is operated in

$$\Delta V_{FET} = \frac{\Delta Q}{C_T} G_{FET} \tag{2.10}$$

Where ΔQ is the signal charge level, C_T is the total output FET capacitance (usually ~10 fF for low noise CCDs) and G_{FET} is the gain of the output FET (usually ~0.7). This readout process is repeated for each pixel of the CCD. Usually a value of 1-6 μ V per electron is obtained.

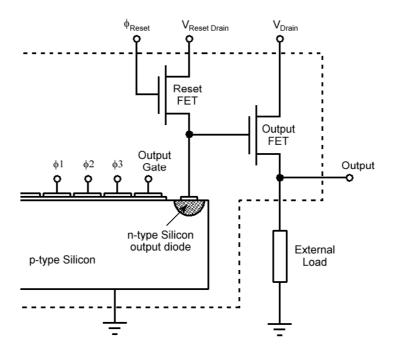


Figure 2.12 Atypical CCD readout register and output circuit

2.6. CCDNoise

Themaincomponents of CCD noise are discussed in detail by Beynon and Lamb (1980), Howes and Morgan (1979) and Robbins (1992). The total CCD noise figure is the quadrature sum of the following sources:

2.6.1. PhotonShotNoise

Themeannumber of electronhole pairs, n_{eh} , created in siliconfor a given incident X-ray photon of energy, E_{π} is:

$$n_{eh} = \frac{E_{\gamma}}{\omega} \tag{2.11}$$

Where ω is the energy required for generation of a single electron-hole pair. For silicon ω is $3.68\,\mathrm{eV}$ at $-100\,^{\circ}$ C and $3.65\,\mathrm{eV}$ at room temperature (Bertolini and Coche 1968). This value is higher than the silicon band-gap energy of $1.12\,\mathrm{eV}$ as phonons are produced as well as electron-hole pairs. The statistical variation of n_{eh} given by Poissonian statistics is higher than the observed variation. The difference is due to secondary electron-hole pair generation not being independent and an empirical modifier to the Poissonian value, called the Fano 1947). The photon shot noise is the reforegiven by:

$$\sigma_{shot} = \sqrt{Fn_{eh}} = \sqrt{\frac{FE_{\gamma}}{\omega}}$$
 (2.12)

To enable X-ray spectroscopy, the overall CCD system needs to ha ve a noise level not much greaterthanthis Fano-Limited value. Fisusually taken to be 0.115 (Alige tal. 1980).

2.6.2. ResetNoise

Due to thermal noise in the reset potential. At-90 °C the reset noise can be ~100 electrons. The reset noise is given by:

$$\sigma_{reset} = \frac{\sqrt{kTC_T}}{q} \tag{2.13}$$

This source of noise can be removed by use of Correlated Double S ampling, CDS, where the reference voltage is measured and averaged over a finite t ime both before and after charge is clocked onto the output node, the difference between the two levels being the signal charge component (Hopkinson and Lumb 1982).

2.6.3. TransistorNoise

Due to thermal motion of charge carriers, 'Johnson' noise, and the trapping and release of electrons in the conductive drain to source channel of the output F ET, 'flicker' noise. Flicker noise is also known as '1/f' noise due to its spectral distribut ion which is proportional to 1/f where α is close to unity (Sze 1981). Both sources of transistor noise c an be optimised by accurate CDS methods (Hopkinson and Lumb 1982).

2.6.4. TransferNoise

Duetolossofsignalchargetotrappingsites.Forsmalllossesthetr ansfernoiseisgivenby:

$$\sigma_{CTI} = \sqrt{N_e N \varepsilon} \tag{2.14}$$

Where N_e is the number of electrons in the signal packet, N is the number of transfers and ε is the CTI.

2.6.5. DarkCurrent

Due to thermal excitation of electrons into the conduction band. These electrons will become added to the signal charge packet introducing a noise component that is dependent on the intrinsic carrier concentration, n_i , and therefore temperature. Electrons can be thermally exc ited into the conduction band from three locations within the CCD: from the depletion region, from the bulk silicon field-free region and from the Si-SiO 2 interface. The total dark current, I_d , is given by (Sze1981):

$$I_{d} = \left(\frac{qn_{i}}{2\tau}\right)D + \left(\frac{qD_{n}}{L_{n}N_{A}}\right)n_{i}^{2} + \frac{qsn_{i}}{2}$$
 (2.15)

Depletion Field-free Si-O₂ region region interface

Where τ is the effective lifetime in the depletion region, D_n is the diffusion constant, L_n is the electron diffusion length and s is the surface recombination velocity. The dark current components from the depleted region and the interface have a temper ature dependence of $\exp\left(\frac{-E_{si}}{2kT}\right)$, where E_{si} is the silicon band-gapener gyof 1.12 eV. The temperature dependence of the dark current component from the field-free region is $\exp\left(\frac{-E_{si}}{kT}\right)$. The dominant component of the total dark current is from the interface region.

Itiscommonpracticetooperatescientific CCDs at allowt emperature to reduce the dark current contribution to the overall CCD noise figure. Operation of a CCD at -90 $^{\circ}$ C has been demonstrated to reduce the dark current by 3 $\times 10^{-6}$ (Chowanietz 1987). The use of 'inverted mode' operationals or educes the dark current by suppressing the contribution from the interface region. The surface of the device is put into inversion, allowing the accumulation of holes at the interface, which then combine with the rmally generate delectrons from interface generation sites, reducing the dark current by a factor of >100. Dark current is d is cussed in more detail in Chapter 3.

2.7. PhotonDetection

Accounting for the electrode structure and oxide layers above th e bulk silicon, a CCD is an efficient detector in two distinctenergy bands. These bands fa llinthe visible wavelengthrange, 4000Åto10000ÅandtheX-raywavelengthrange,1keVto5keV.Theabs orptionefficiency of siliconat different wavelengths is shown in Figure 2.13. When a nX-rayphotoninteractswith the bulk silicon of the CCD a cloud of electron-hole pairs is p roduced as a result of ionisation. This is a threshold process that has a weak temperature d ependence. At room temperature the ionisationenergyis~3.65eVincreasingto~3.72eVclosetoabsolute zero(BertoliniandCoche 1968). The number of electron-hole pairs produced by ionisation is there foreproportional to the incidentphotonenergyforenergiesaboveafeweV.

Optical photons are of a relatively low energy and interact with electrons in the valence band of the silicon, promoting electrons to the conduction band via the photoel ectric effect. In this way a single electron is generated for each incident optical photon. The electrons can then move freely in the silicon to be collected in the potential wells under biased CCD electrodes, the number of electrons in a given pixel being proportional to the intensity of the incident adiation.

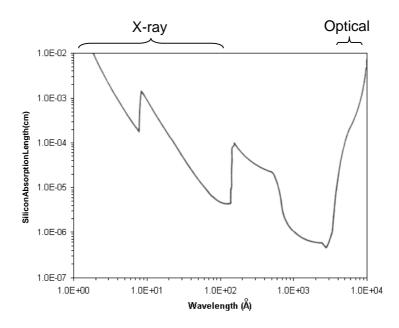


Figure 2.13 The absorption length of electromagnetic radiation in silicon

If an incident photon imparts some of its energy directly to a si licon atom, it may excite an electron in the K-shell, expelling it from the atom. The emitte delectron will have the same energy as the incident photon, minus the silicon K-shell binding ener gy of 1.84 keV. The atom then de-excites by transfer of an outer shell electron to the K-shell, releasing a fluorescence X-ray, orby Augerand non-radiative processes. Fluorescence X-rays in licon have an energy of 1.7 keV and are absorbed by ~ 10 μ mof silicon, before they can travel into an adjacent CCD pixel contributing to the escape peak in the X-ray spectrum.

2.7.1. ChargeSpreading

each pixel, forming the signal packet, while holes are swept aw fieldfree region charge spreading occurs before the electrons

This process may result in some electrons being collected in s interaction pixel causing a distortion in the CCD image. When obser a CCD it is usual to consider only 'isolated events', pixels w it to get the best spectral resolution. A spectrum of 'all events spectral features as a result of charge spreading, degrading t increasing the spectral resolution is to use software that recognitions.

ay by the electric fields. In the arepulled into the buried channel.

urrounding pixels and not the ser vingaspectrum recorded by ithnocharge in the adjacent pixels,

' will increase the width of the he resolution. One technique of ognises 'split-pixel' events and sums

the charge in the central and adjacent pixels, recovering the The effect of charges preading can be reduced by minimising the the device.

incident photon energy information. extent of the field free region of

2.7.2. Quantum Efficiency

The efficiency of a CCD to detect photons of different wavele ngth is called the 'quantum efficiency',QE.TheQEatagivenenergy, *E*,isgivenby:

$$QE(E) = T_{electrode} \left(1 - e^{-\mu x} \right) \tag{2.16}$$

Where $T_{electrode}$ is the transmission of the electrode structure, μ is the absorption coefficient of silicon and x is the thickness of the epitaxial silicon layer of the de x is the transmission of the electrode device. An example of a CCD QE curve for a CCD22 open electrode device optimised for X-ray spectroscopy is shown in Figure 2.14. The absorption edges are due to photons being absorbed by elect rons in the inner shells of the silicon atom. The absorption edges are also where the photoelectron causes variations in the QE attributable to abs orption fine structures (Keay 1997).

The QE at low energy is decreased as photons are absorbed by the electrode structures before passing into the bulk silicon of the device where the charge ge nerated can be collected. An improvementinthelowenergyQEcanbeachievedby 'backillumination' of ade vice(Shorteset al. 1974). This involves thinning the bulk silicon on the back of the **CCD**downtothedepletion layerboundaryduringfabrication. The resulting device can be backilluminatedwithlowenergy photons being absorbed in the bulk silicon after passing through a dea dlayer of only ~50 nm, improving the QE. An example QE curve for a back illuminated dev ice is also shown in Figure 2.14. Other methods of improving the low energy QE are use of thin and open electrode structures (Castelli 1991, Hollandet al. 1993). The high energy Q Ecanbeimprovedbyusinga higher atomic number material as the detector, for example GaA s, or in the case of the silicon CCD, increasing the depletion depth by using higher resistivity silicon.

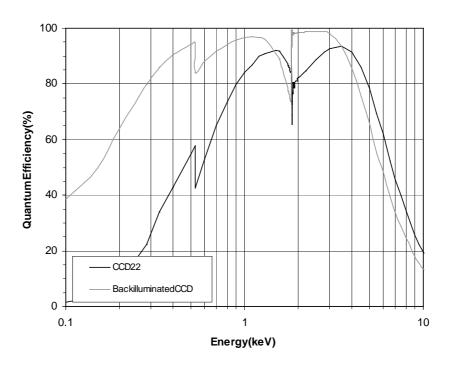


Figure 2.14 Quantum efficiency of an E2V Technologies CCD22 open electrode de vice (Short 2002). The quantum efficiency of abackilluminated device is also shown for com parison

The 'response matrix' of a CCD describes the probability dist ribution of the CCD channel in which aphoton of a given energy will be measured. An example of am foran E2VTechnologies CCD12 device is given in Figure 2.15. The gre logarithmic scale and represents the QE for a given photon ener gy and CCD channel. A logarithmic scale is used to emphasise the second order loss effect s.

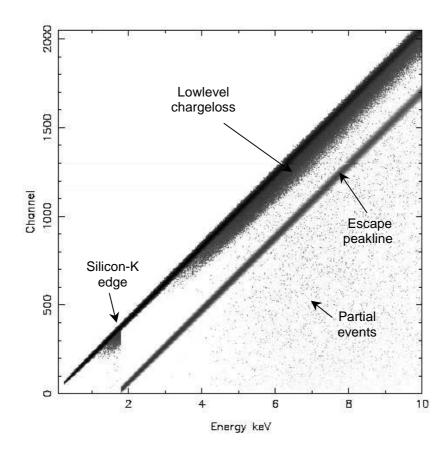


Figure 2.15 An E2V Technologies CCD12 response matrix depicting the signal 1 evel in channels, for a given in put photon energy

2.7.3. SpatialResolution

The spatial resolution of a CCD is described by the 'modulation t modulation depthis the difference in charge level between two sour level between them. The MTF is the relationship of the modul frequency. The MTF is degraded by charge transfer losses and al quality astronomical CCD needs sources to be separated by more MTF.

ransfer function', MTF. The ces, and the minimum charge ation depth to the image spatial sobycharges preading. A good than two pixels to have a high

2.7.4. EnergyResolution

The energy resolution of a CCD is described by the `full wid that half maximum', FWHM of a spectral feature. For a cooled CCD with good CTE, the FWHM is given by:

$$FWHM = 2.35\omega \sqrt{\sigma_{total}^{2} + \frac{FE_{\gamma}}{\omega}}$$
 (2.17)

Where σ_{total} is the total CCD readout noise in electrons. Typically ⁵⁵FeK αpeak. FWHMof~140eVforthe

 σ_{total} is ~10 electrons giving a

he operational

2.8. **Summary**

characteristicsofCCDs.

This chapter has described the CCD manufacturing process and presentedtheunderlyingphysics governing charge storage, charge transport and charge readout of a device. Both surface and buriedchanneldeviceshavebeendescribed.buriedchanneldevices featuringintheworkcarried out for this thesis. The various sources of noise involved wit h CCD operation have also been discussed along with the definition of several important terms used to describe the operating characteristics of a device. The next chapter goes on to descri be the various components of the space radiation environment and the effects this environment has on t

Chapter 3: The Space Radiation Environment and its Effects on CCDs

This chapter describes the near Earth space radiation environment and its effects on the operational characteristics of CCDs. The different components of environment are described, followed by a detailed discussion of the mechanisms relevant to CCDs and their resulting effects on CCD operation.

3.1. Introduction

For the operation of CCDs on scientific satellites and spac ecraft, it is necessary to have an understanding of the radiation environment the devices will experie nceduringtheirlifetimeand to have a thorough understanding of the effects this environment wi ll have on the operational characteristics of the devices. This chapter will first discuss the various components of the space radiationenvironmentandthendescribethetworadiationdamagemechani smsrelevanttoCCDs: ionisation and displacement damage. After presenting the underly ing physics behind the two damage mechanisms, the effects of radiation damage on CCD operat ion are described in detail, along with techniques and methods of reducing radiation damage; 'r adiation hardening'. A number of models used to simulate both the space radiation environment and radiation damage effectsinCCDsarealsodiscussedinthischapter.

3.2. The Space Radiation Environment

The different components of the space radiation environment are discussed in detail by Holmes-SiedleandAdams(2002). What follows is a brief summary of the main space radiation components that influence CCDs on board spacecraft orbiting the Ear th. The effect of geomagnetic and spacecraft shielding on the radiation fluxes received by a CCD are then discussed, along with an overview of some of the modelling tools avaccumulated spacecraft radiation fluxes.

3.2.1. RadiationBelts

The radiation belts consist of protons up to a few hundreds of MeV

MeV that have become trapped in the Earth's magnetic field w
the solar system. The belts were discovered by Van Allen in 195

8(Van Allen and Frank 1959)

and are described in detail by Hess (1968). The trapping of protons an delectrons occurs where the magnetic field lines come close together and is dependent on theincoming particle's energy and angle of incidence. Once trapped the particless piral around the magne ticfieldlinesbouncing backandfourthbetweenthemagnetic poles. The final component of tr appedparticlemotionisa longitudinal drift around the Earth, electrons drifting east and protons drifting west. Figure 3.1 illustratesthemotionofachargedparticletrappedinthe Earth's magnetic field. The channelling of particles down into the atmosphere by the strong magnetic field regions above the north and south poles gives rise to colourful aurorae, their colours caused by electrons colliding with molecules in the atmosphere.

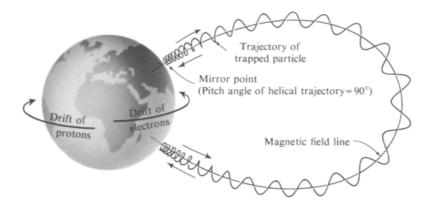


Figure 3.1 The motion of charge particles trapped by the Earth's magnetic field (Hesss 1968)

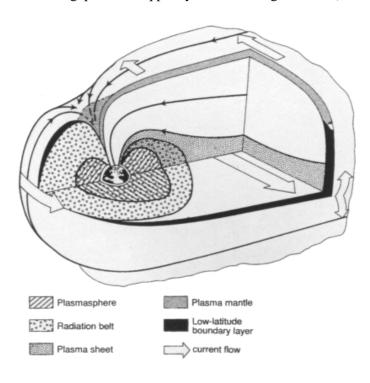


Figure 3.2 The Earth's magnetosphere and radiation belts (Daly 1989)

Figure 3.2 shows the 'bow wave' form of the Earth's magnetosphere and the regions where particles become trapped forming the radiation belts. The asymme trical form of the magnetosphere is a result of distortions caused by the solar wind, the ~11 ° offset of the Earth's magnetic axis from its rotational axis and also geological ef fects. The general shape and the distortions in the magnetic field create areasof increase dtrapped particle flux over the north and southpoles, called the 'auroral horns'.

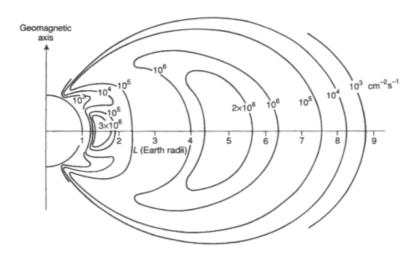


Figure 3.3 Aradial profile of the trapped electron flux in the Earth's radiation belts for electrons of energy above 1 MeV (Daly 1989)

Radial profiles of the proton and electron belts have been produced fr om a number of on-orbit measurements (Daly 1989). The trapped electron flux is highest in two altitude bands called the 'inner' and 'outer' zone maxima, shown in Figure 3.3. The inner zone cont ains electrons of energies up to ~5 MeV while the outer zone, with a flux around an order of magnitude higher, containselectronsofgreaterthan~7MeV.Thelowfluxareabetwee ntheinnerandouterzoneis called 'the slot'. The highest concentration of protons is found a t lower altitude, shown in Figure 3.4. Unlike the trapped electrons, the trapped protons do not for m distinct zones. The proton flux varies inversely with distance from Earth and monotonica lly with energy (StassinopoulosandRaymond1988). The variation of the electron and proton flux eswit hparticle energy are shown in Figures 3.5 and 3.6 respectively, for a low Ea rthorbitofinclination 60 300kmand500km.

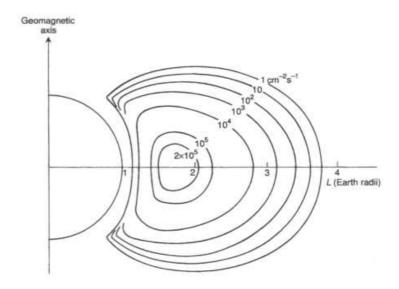


Figure 3.4 Aradial profile of the trapped proton flux in the Earth's radiation belts for protons of energy above 10 MeV (Daly 1989)

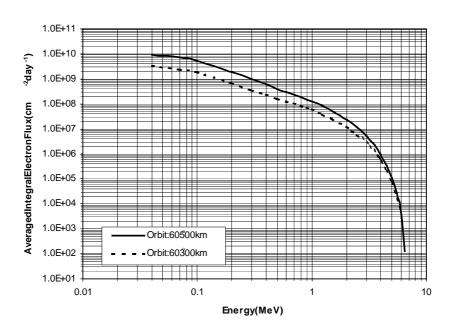


Figure 3.5 Variation of the trapped electron flux with particle energy in the Earth's radiation beltsmodelledby AE8

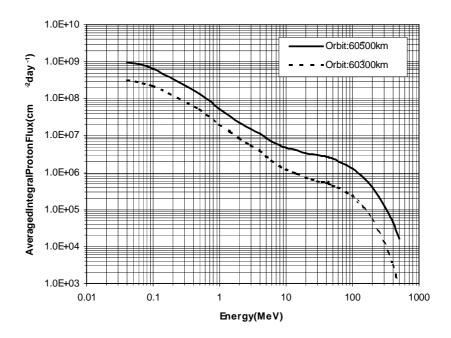


Figure 3.6 Variation of the trapped proton flux with particle energy in the modelled by AP8

For a spacecraft orbiting the Earthitis important to spend as little time in the radiation belts as possible as the total incident spacecraft radiation flux is s trongly dependent on the orbital parameters. Low Earth orbits with inclination > 45 ° will pass through the auroral horns and be subjected to the trapped particle environment (Stassino poulos and Raymond 1988).

3.2.1.1. TheSouthAtlanticAnomaly

In the same way the Earth's magnetic field creates the au roral horns, a magnetic anomaly is responsible for increasing particle fluxes by a factor > 100 in a region over the South Atlantic. This region is known as the South Atlantic Anomaly, SAA. Figure 3.7 shows a 500 km altitude contour plot of proton fluxes > 50 MeV over the South Atlantic, revealing the dipping of the proton belttowards the Earth's surface in this region. The SAA is import ant not only for satellites in low Earthorbit, but also for the many space craft launched that the infinal destinations. The SAA and aroural horns can only be avoided by satellites in low Earthorbits of inclination < 15 of (Stassino poulos and Raymond 1988).

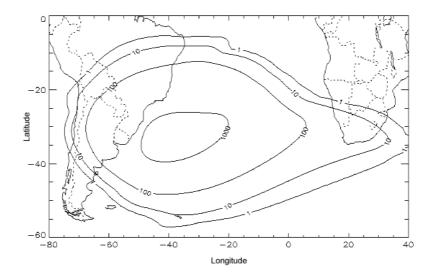


Figure 3.7 A 500 km altitude contour plot of proton fluxes >50 MeV produced by the A radiationmodelshowingthedippingoftheprotonbeltintheSouthPacificformi ngtheSAA

3.2.2. SolarWind

Thelighterelements in the Sun's coronahave enough energy to be ejected out into space forming the 'solar wind' (Parks 1991). The ejected particles consist mainly of protons and electrons of a few keV and their flux is inversely proportional to the distanc efrom the Sun squared and may vary by a factor ~20 dependent on the 11 year solar cycle. Beyond the magnetosphere the solar wind can be of considerable flux that can cause space craft charging.

3.2.3. SolarEvents

Energetic protons, heavy ions and electron sup to MeV energies ca nbeejectedintospacebythe Sun as a 'solar event' (Tranquille 1994). The flux of particles emitted is intermittent and depend ant on the solar cycle making it difficult to predictthe future occurrence of solar events. Figure 3.8 shows solar event and sunspotactivity over 3 solar cyc les. Asolareventtakes around 8 minute store a chthe Earth and can last for a few hours to a few days in the contract of tduration. The protons in a solar event are of lower energy than the trapped protons in theEarth's radiation belts, but they can have much higher total fluence levels. For spacecraft or bi tingbeyondtheradiationbelts, for example in geostationary, highly eccentric or planetary orbits, a substantial part of the total spacecraftradiationfluxwillbecausedbysolarevents.

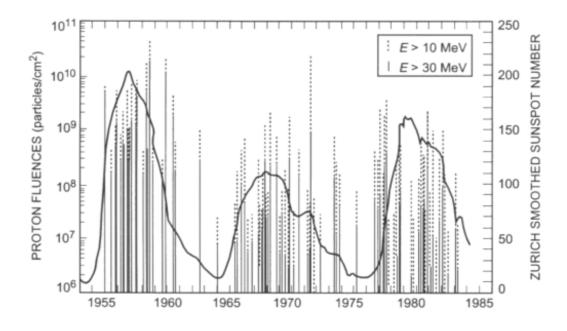


Figure 3.8 Monthly Solar event and sunspotactivity over 3 solar cycles (Goswamie tal. 1988)

3.2.4. CosmicRays

Cosmicraysarehighlyenergeticchargedparticlesoriginating from threepossiblesources:

- Galactic:Theseparticlescomefromoutsideoursolarsystemem ittedfromsupernovae, pulsarsandneutronstars.Onpassingthroughthegalacticmagneticfieldthe particles becomediffuseandonarrivalatEarththeyareseenasalowisotropicflux. Theparticles aremostlyprotonswith~1% heaviernucleiofuptoTeVenergies.
- Solar:TheseparticlescomefromtheSun'schromosphereandareemitted insolarevents.

 Thecompositionofsolarcosmicraysisdifferenttothatofgalacticcosm icraysasa resultoftheirdifferentorigin.
- Terrestrial:GalacticcosmicraysinteractwiththeEarth'sat mospherecausingsecondary radiationtobeemittedasa'cosmicrayshower'.Thissecondaryradiati onisthemain componentofcosmicradiationattheEarth'ssurface.

The cosmic ray flux is attenuated by the solar wind and therefore is seen to vary with the solar cycle.

3.2.5. GeomagneticandSpacecraftShielding

AdegreeofprotectionfromlowenergyradiationisprovidedbytheEarth's magnetosphere(Daly 1994,StassinopoulosandRaymond1988).Cosmicraysandparticlesfromthe Sunneedtohave aminimumenergyforpenetrationintothemagnetospherewhichre sultsinthelowerintensity of these particles nearer the Earth. The amount of shielding offer ed by the magnetosphere is dependentonthealtitudeandinclination of a spacecraft's or bitandals other intensity of the solar wind, which can compress the magnetosphere allowing particles to pene trate further. Geostationary and polar orbiting spacecraft will not experience any benefits of geomagnetic shielding as they are beyond or at the limits of the magnetosphere.

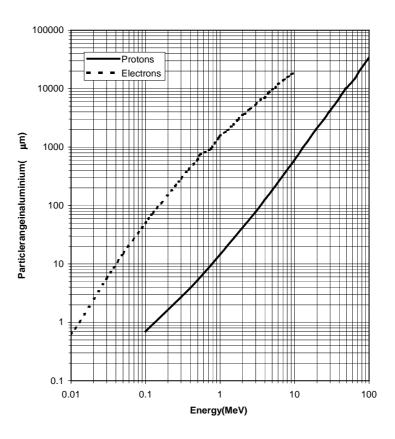


Figure 3.9 The range of protons and electrons in a luminium (Ziegler et al. 1985)

Physically shielding CCDs on a spacecraft by surrounding them w ith aluminium, or a high atomic number metal such as tantalum, is a common method used to reduce the expected total mission radiation fluence (Daleet al. 1993). The range of elect rons and protons in aluminium is

shown in Figure 3.9 (Ziegler et al. 1985). Electrons of up to ~5 Me V can be shielded out by ~5mmofaluminiumorequivalentthicknessofspacecraftstru cture, for example any electronics or optics structure, greatly reducing the electron component of a spacecraft's total radiation fluence when orbiting within the radiation belts. Higher energy par ticles associated with solar events and cosmic rays are difficult to shield practically and are therefore an important factor when modelling the expected CCD radiation fluence. The use of spa cecraft shielding also introducesasecondaryradiationcomponentwheretheenergyandfluxofthe particlesischanged through scatter and absorption in the shield material. This compone nt also has to be considered when modelling CCD radiation fluence.

The CCD may be unshielded in the observation direction and for thisreason the choice of orbit and orientation of the spacecraft are important. Some instruments , for example the X-ray Telescope onboard the NASA Swift Gamma Ray Burst Explorer sate llite, employ the use of mechanical shutters that can be closed to prevent radiation enteringthetelescopethatcouldcause damage to the detectors (Burrows et al. 2000), while another tec hnique used by the EPIC instruments on the XMM-Newton satellite involves having a 'cl osed' position on the instrument's filter wheel (Turner et al. 2000). The use of shutt ersisavaluable way of protecting CCDs when travelling through high radiation flux areas, but does howev er introduce added complexity and mass to the spacecraft.

3.2.6. ModellingtheSpaceRadiationEnvironment

To model the expected radiation fluence to be received by a CCD during aperiodin space it is necessary to have a model that will use the orbital paramete rs of the spacecraft, integrating the expected particle fluxes as the spacecraft travels around its orbit for the duration of its mission. The model needs to include information on trapped particles in the Earth's radiation belts, solar event particle fluxes, cosmic rays and the effects of spacec raft and geomagnetic shielding. One suchmodelistheSPaceENVironmentInformationSystem,SPENVIS, whichwasdevelopedby the European Space Agency in 1998 to incorporate several space rad iation models into a single interface (Heynderickx et al. 2000). Orbital parameters are entered into the program and then required models are selected by the user for evaluation of the radiation environment over a specified mission duration. After selection of the spacecraft orbit, trapped proton and electron fluxes are predicted using the incorporated AP8 and AE8 models, alongwithaprediction of the solarprotonfluenceusingeithertheKing,JPL-85orJPL-91 models .Theeffectofgeomagnetic shieldingcanbeincludedwhichcomputesanenergycutoffdependent ontheorbitalparameters and solar cycle epoch, while the effect of different thickne sses of shielding around a CCD is modelled by SHIELDOSE. The SHIELDOSE model currently only incorpo rates aluminium shielding but is being expanded to include additional materials. The whole SPENVIS package can be used to obtain a first order approximation of the total radiation fluence expected to be received by a CCD during its operational lifetime.

Themaindrawbackofusingthecomputational models within SPENVISres ults from the data the models are based on having been recorded many years ago, for example the AP8 and AE8 models used at a from the 1960's which introduces large uncertaint ies. There is currently a drive to include more recent satellited at a in the space radiation environment models and to use recent data to correct existing models. The Trapped Radiation ENvironment model Development project, TREND, has been initiated by the European Space Agency T echnology Research Programme to improve upon the existing space radiation environment mode Is of spacecraft orbiting around the Earththrough the radiation belts (Lemaire et al. 1995).

Anotherproblemwithcurrentradiationmodelsiscausedbythespora dicnatureoftheamplitude and frequency of solar events. Particles from solar events are hard to shield out due to their high energy spectrum, and hard to detect be for ecausing damage to a CCD. Radiation model sthere for egenerally incorporate either a single major solar event, or a specific number of events for a certain mission duration, giving a worst case estimate for the solar event.

3.2.7. TheNon-lonisingEnergyLossFunction

When discussing total proton fluence values it is useful to talk in terms of equivalent 10 MeV fluence, to allow the comparison of irradiation experiments carrie dout at different proton energies. The Non-Ionising Energy Loss function is a scaling fact or that allows the amount of displacement damage caused by protons of different energiest obe compared. The use of NIEL scaling for silicondevices has been described in detail by Burke (1986) and Van Lint (1987). The specificuse of NIEL scaling in CCDs is discussed by Srouretal. (2003)

The form of the NIEL function is shown in Figure 3.10 and can be approximated by:

$$E_p < 13.5 \text{MeVthen}$$
 NIEL= $\frac{8}{E_p^{0.9}}$ (3.1)

$$E_p > 13.5 \text{MeVthen}$$
 NIEL= $\frac{1.6}{E_p^{0.28}}$ (3.2)

Where E_p is the incident proton energy in MeV.

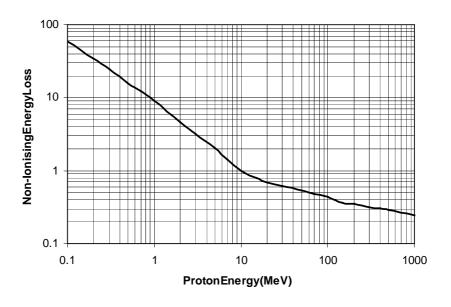


Figure 3.10 The Non-Ionising Energy Loss (NIEL) function

3.3. RadiationDamageMechanismsintheCCD

Theeffectofradiationonsilicondevicesisdiscussedindetai linanumberofbooks, for example Srour(1984), Larin(1968) and Holmes-Siedleand Adams (2002). The two diagrams amage mechanisms important for the study of radiation effects in CCDs are ionisation damage e, affecting devices with oxide in sulating layers, and displacement damage, which affects all semi conductor devices.

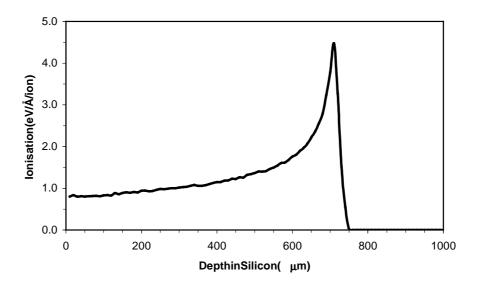


Figure 3.11 The amount of ionisation caused by a 10 MeV proton in silicon modelle d using SRIM2003

3.3.1. IonisationDamage

Ionisation damage occurs when an incident particle can impart enough energy to an atom to excite an electron into the conduction band. As the particle travel sthrough the CCD it leaves a trailofelectron-holepairsalongitspath. Figure 3.11 shows how theam ountofionisationcaused by a 10 MeV proton varies with depth in silicon. This is a thre shold process with an energy of ~3.65eVrequiredtoexciteanelectronintotheconductionbandofas iliconatomand18eVfor a silicon-dioxide atom (Emery and Rabson 1965). In the silicon of the device the holes are quicklyremovedbytheelectricfieldsandtheelectronsare collectedinthepotentialwellsunder the electrodes where they become part of the signal charge. In t he oxide and nitride insulating layersmostelectronswillrecombinewithholesbutsomecarri erswillbelefttodriftanddiffuse throughthelatticeundertheinfluenceoftheappliedelectric fields. The electrons are swept from the device while some of the holes will become trapped near the Si-SiO₂ interface where the concentration of impurity atoms is high. Impurity atoms in the s ilicon lattice have associated discrete energy levels that lie between the conduction and val ence bands and it is here that carriers become 'trapped' (Grove 1967). The holes may be therm allyexcited and released from the shallow trap sites, drifting through the lattice again unti lbecoming trapped at deeper levels. Holestrappedatadeeplevelwillremaintrappedforalongerperiodof timeresultinginachange

in the electric field potential at the Si-SiO 2 interface. The increase in positive charge by the accumulation of holes results in an increase in the observed le akage current of the device. If the device is unbiased during irradiation the electrons in the oxide and nitride layers are free to diffuse around allowing more recombination to occur and reducing the amount of leakage current generated (Robbins 1992). Figure 3.12 shows the amount of radiation induced charge that escapes recombination for different irradiation bias.

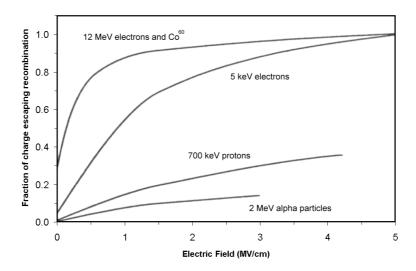


Figure 3.12 The amount of radiation induced charge escaping recombination at d ifferent irradiationbiaslevels(Robbins1992)

3.3.2. DisplacementDamage

Displacement damage is caused when an incident energetic photon, charged particle or neutron imparts enough energy to an atom to displace it from its latti ce site (Messenger 1992). Atomic displacement is a threshold process requiring ~20 eV in silicon. T he absence of an atom in the lattice is called a 'vacancy' and the displaced atom is c alled an 'interstitial' atom, the two components forming a 'Frenkel pair'. If the displaced atom has enoug henergy, it may displace surrounding atoms creating a 'defect cluster'. Neutrons with energ ies of a few MeV can cause clusterdamageinsilicondisplacinghundredsofatoms, while MeV energyelectronsandprotons usually only impart enough energy to the target atom to cause an is olated defect. Figure 3.13 showshowthenumberofdisplacedatomsdecreases withincreasing incident proton energy. For low incident particle energies, energy is imparted to the tar get atom by Coulomb interaction. For incident particle energies ~ 10 MeV the energy is transferred by ela stics cattering from the nuclear force field, while a tenergies of > 100 MeV the transfer is by an uclear in elastic process.

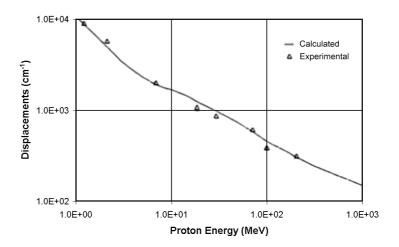


Figure 3.13 The number of atoms displaced by different energy protons in silicon (Van Lint 1987)

Defects in a CCD are also created during the manufacturing pr ocess which includes a high temperature,~1000 °C,annealingphasetoremovemanyofthem. There are an umber of known defects that can be present in CCD devices, each with a distinctive activation energy and annealing temperature, most of which can be annealed at around room temperature. Using activation energy and anneal temperature measurements the domina interest can be determined.

The vacancies and interstitial sites created by displacement dama geare not electrically active, but if they possess thermal energy > 100 °K they can move through the crystal lattice and combine with other defects to create stable defect complexes. The defect to complexes of importance in CCDs are illustrated in Figure 2.2, along with some of their properties. The three main complexes are the phosphorous - vacancy, the oxygen - vacancy and the divacancy although the rear ean umber of other impurities that can form defects, including boron, carbon and aluminium atoms. The defects created have associated discrete energy levels, which have lie within the silicon band-gap

(Grove 1967). These radiation-induced levels can give rise to five processes: recombination, generation, trapping, compensation and tunnelling. Any amount of each proces s can occur dependent on the carrier concentration, temperature and location in t he device. Each of these processes is illustrated in Figure 3.14, and is described below:

- Recombination: Electron-holepairs recombine at a rate dependent on the type of decentre, reducing the minority carrier lifetime.
- Generation: Thermalgeneration of electron-holepairs near the middle of the band-gap.
- Trapping:Carriersbecometrappedatshallowlevelsintheband-gapandcanbere -emittedby thermalexcitation.Therateofre-emissionisdependentonthetypeofde fectcentre.
- Compensation: Reduction of the majority carrier concentration by carriers becoming trapped at lower levels it es from donors it es just below the conduction band.
- Tunnelling:Carrierscantunnelthroughapotentialbarrierfromthevalence bandtothe conductionband.Thisprocessisonlyimportantwheretheelectricfieldst rengthisgreater thanafew10 ⁷Vcm ⁻¹andthereforedoesnotcauseaproblemduringusualCCDoperation.

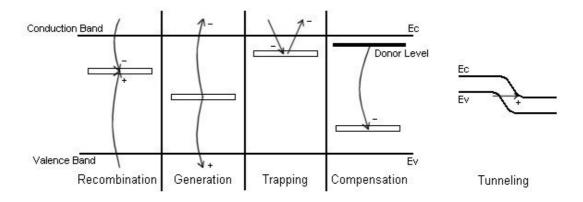


Figure 3.14 The possible effects of radiation induced levels in the silicon band-gap

3.4. The Effects of Radiation Damage on the CCD

Ionisation and displacement damage have a number of effects on the operational characteristics of the CCD that are described below. Methods of preventing and reduc ing the radiation damage caused to adevice are also discussed.

3.4.1. FlatBandVoltageShift

As a result of the increase in positive charge at the Si-S iO₂ interface caused by ionisation, the reset drain voltage has to be made more negative for the devi ce to operate in the same manner. This change in threshold voltage is termed a 'flat band volta ge shift'. Figure 3.15 shows the effect of oxide trapped charge on the potentials under the char ge transfer electrodes and output structure of a CCD. The build up of positive charge does not e ffect the storage and transfer of collected charge because all the electrodes are affected similarly, the potential of the reset drain however has no insulator above it and therefore needs to be made morenegative to compensate for the reduced electrode and output gate potentials (Roy et al. 1989). A flat band voltage shift reduces the charge hand ling capacity of the CCD and increasesthedevicepowerrequirement.If alarge enough shift occurs as a result of ionisation damaget hedevice may be come in operable. Figure 3.16 shows the flat band voltage shift resulting from a 50 kra d proton irradiation of an $E2VCCD01. The {\it measurements} were recorded by monitoring the current$ of the reset drain and recording at what point the current drops, indicating the point at w hich charge is no longer transferred.

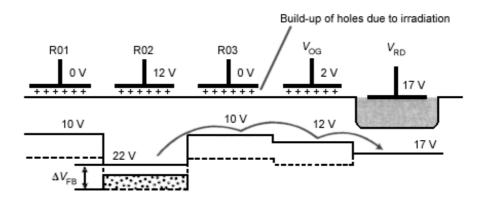


Figure 3.15 The effect of oxide trapped charge on the potentials under the charge transfer electrodesandoutputstructureofaCCD(adaptedfromRoyetal.1989)

Methodsemployedtoreducetherequiredchangeingatevoltagecausedbyionisa tiondamageare called 'radiation hardening' techniques. Methods include thinning of th eoxidelayerreducingthe number of trapping sites present (Shiono et al. 1983), high temperatu reannealing of the device duringmanufacturetoremovealargefractionoftheoxidetrappingsites, use of ap-channelCCD structurewheretheholesaresweptawayfromtheSi-SiO 2interface, and use of a planar insulator $so the voltage shift is the same under all electrodes \, of t \,$ hedevice. The injection of charge into a devicehas also been demonstrated as a successful method for 'f illing'traps, removing the holes accumulated at the surface of the device. Charge injection is disc ussedinmoredetailbelowwhen describing methods to prevent CTI degradation. During CCD operation, reducing the operating temperature can reduce the level of ionisation damage induced leakage current by 'freezing' carriers intrapsites, increasing the carrier emission time c onstant.

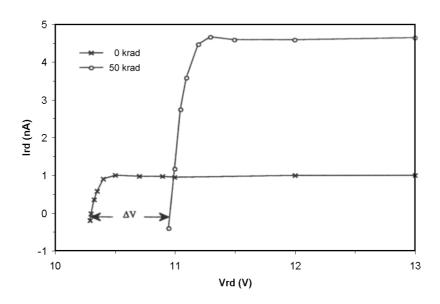


Figure 3.16 The flat band voltage shift resulting from a 50 krad proton i rradiation of an E2V CCD01, where Vrdistheresetdrain voltage and Irdistheresetdrain curren t(Robbins 1992)

3.4.2. IncreaseinDarkCurrent

Theincreaseinsurfacechargeasaresultofionisationda mageina CCD rathe observed dark current of the device. An additional increase in the dathe generation of carriers from radiation induced levels in the rate equations for defects in the depleted and bulk regions of a CCD are

mageinaCCDresultsinanincreasein
se in the dark current results from
silicon band-gap. The generation
CCD are discussed in detail by

Robbins (1992). The contribution to dark current from the depleted and bulkregionsoftheCCD are roughly equal, although in the depleted region it is the result of a large number of shallow trap semitting small amounts of charge while in the bulk region thedarkcurrentisgeneratedbya fewdeeperleveltrappingsitesemittinglargechargelevels(B urt2002). Although there is no way to suppress the dark current generated in the bulk silicon of a device, the accumulated surface charge can be reduced by holding the surface in inversion. With th e surface of a CCD in inversiontheholesareattractedfromthechannelstopsfilli ngthetrappingsitesintheinsulating layers of the device. The dark current spectrum is Gaussian in nature with a high energy tail composed of 'dark current spikes'. The nature of dark current spikes is dis cussedbelow.

3.4.3. IncreaseinChargeTransferInefficiency

Energy levels in the silicon band-gap generated by displacement da mage of a CCD can trap charge carriers resulting in a loss of signal charge as charge is held from its associated signal packetduringreadout. The trapping time is dependent on the conce ntrationandemissionrateof the defect involved. Figure 3.17 shows the approximate variation i n emission rate for several commondefects as a function of temperature. For devices operating at opti calwavelengthsandat TV framerates, the CTI can be decreased by radiation damag ewithoutsignificantlossofimage quality. The apparent loss in CTI can be decreased by thermal ge neration of charge filling the trapsinplaceofsignalcharge(Hopkinson1992,Holmes-Siedleetal.1995)orchar geinjection.

Anumber of techniques have been developed to measure the CTI of a method involves measuring the delay in charge transfer of a spe stacked line trace' method involves creating an array of his different region of interest on the CCD, and evaluating the CTI by characterising the change in mean energy of an X-ray peak with position across the CCD ar the X-ray peak in the stacked line trace is proportional to the CTI value, the shallower the slope, the lower the CTI.

TheCTIofadevicecanbedecreasedinanumberofways:

 HigherSignalCharge:Areductioninthefractionofsignalchargelosttot rappingisbrought aboutbyhighersignalchargelevels.

- FasterPixelTransferSpeed:ByincreasingtheclockingspeedoftheC CDtofasterthanthe trappingtimeconstantofthepredominanttraps,lesschargefromthesig becometrappedbeforetransferofthecharge.
- HighTemperatureAnnealing:Trappingsitescanbeannealedathightem peraturestoregain somechargetransferperformance(Holland1991).
- LowTemperatureOperation:CTIhasbeenseentodecreasewithdecreasing temperatureasa resultof'freezing'carriersintrapsites(Hollandetal.1991).
- ChangesinDeviceStructure:SuccessfulCTIreductionhasbeenobservedusi ngnarrow channel(Hollandetal.1991)orsupplementarychannel(Bredthaueretal.1991)ele ctrode structureswherethesignalchargeisconfinedinasmallervolumere ducingthenumberof trappingsitesinthevicinityofthesignalcharge.
- DefectEngineering:Severalwaysofreducingtheamountofphosphorous-vacanc adevicehavealsobeeninvestigatedinanattempttoremovethemaincharget rapping mechanismresponsibleforincreasingCTI(Holmes-Siedleetal.1995,Hopkins on1999).
- ChargeInjection:SomeCCDdesignsincorporateastructuretoallowchar getobeinjected intothefirstimagerowofthedevice.Thischargeisthensweptth roughtheimageandstore sectionsofthedevicefillingmanyofthetrapsandreducingtheCTI(Holla ndetal.1993).A variationonthisideainvolvesintegratingsignalchargeinthefirs tfewrowsofadevice beforetheaccumulatedchargeissweptthroughthedeviceonreadout.Thism ethodinvolves noextraCCDstructureandinsteadreliesonanovelCCDclockingmethod(Pri gozhinetal. 2000).

The XMM-Newton spacecraft has taken advantage of narrow electr ode and charge injection structures in the design of the CCDs employed in the two MOS Eur opean Photon Imaging Cameras onboard. Charge injection tests have been investigated in the laboratory while a reduction in operating temperature from -100 °C to -120 °C has been investigated on orbit. Both these techniques have shown beneficial reductions in CTI (Abbeyet al. 2002).

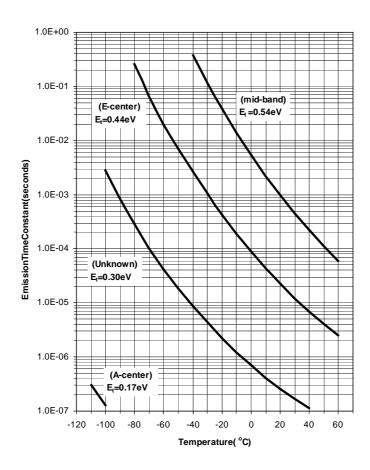


Figure 3.17 The approximate variation in emission time constant with te mperature of several commondefects found in the CCD (Burt 2002)

3.4.4. BrightPixels

Brightpixels, ordark currentspikes, are found to be presentina CC Dpriortoirradiation, butthe number of bright pixels is greatly increased after irradiation, especially with protons. The bright pixel spikes found in unirradiated devices are possibly due to met al precipitates at oxidation-induced faults (Burt 2002) while the spikes found post irr adiation are caused by induced carrier emission sites within the bulk and depleted sili con of the CCD. The amplitude rangeofbrightpixelscoversabroadrangeandisseeninthed ark current histogram of a CCD asa high energy tail on the Gaussian distribution of the CCD darkcurrent. The range in amplitudes results from the different induced midband-gap energy levels ca usedby irradiation of a device, coupled with any 'Field Enhanced Emission' factor. Some bright pixels exhibit a 'switching' behaviour, changing sharply between two or more distinct charge le vels with random time constants. This type of pixel fluctuation has become known as 'Random T elegraph Signal' behaviourandisthesubjectofChapter6below.

3.4.4.1. FieldEnhancedEmission

Fieldenhancedemission can result from three possible mechani sms: the 'Poole-Frenkel' effect, where an electron climbs over a potential barrier lowered by an applied electric field, 'pure tunnelling', and 'phononassisted tunnelling', where an electron absorbst hermalenergy from the lattice and can tunnel through the potential barrier (Martine tal. 1981). These three processes are illustrated in Figure 3.18.

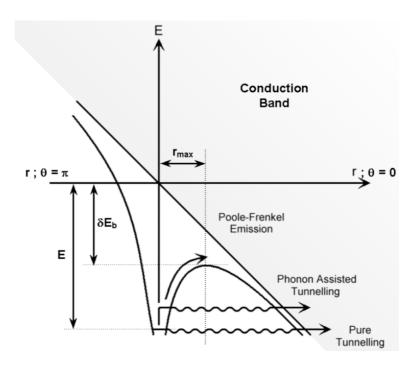


Figure 3.18 The three possible mechanisms of field enhanced emission (adapated from Martinet al. 1981)

In a CCD the electric field strength associated with the chan nel stop and inter-electrode regions of a pixel can be of order 10^{-5} - 10^{-6} V cm $^{-1}$, causing significant field enhanced emission. The enhancement factor for Poole-Frenkel emission in the case of an electron trapped at an energy level E below the conduction band edge, can be obtained by first considering the potential. An electron trapped by a singly charged positive ion, located at r=0, under the influence of a uniform applied electric field, ξ , will experience apotential, V, given by:

$$V(r) = \frac{-q^2}{4\pi\varepsilon_{ii}\varepsilon_0 r} - q\xi r\cos\theta \tag{3.3}$$

Where spherical co-ordinates are used and the arbitrary zero o f energy is taken to be the conduction banded geat r=0, as shown in Figure 3.19 (Hartke 1968). The potential minimum at $r=r_{max}$ is found by setting $\partial V/\partial r=0$, to obtain:

$$r_{\text{max}} = \left(\frac{q}{4\pi\varepsilon_{Si}\varepsilon_{0}\xi\cos\theta}\right)^{\frac{1}{2}} \tag{3.4}$$

Evaluating Vat $r = r_{max}$ gives an expression for the reduction in the potential barrierhe ight, δE_b , due to the presence of an applied electric field:

$$\delta E_b = q \left(\frac{q \xi \cos \theta}{\pi \varepsilon_{Si} \varepsilon_0} \right)^{\frac{1}{2}}$$
 (3.5)

Integrating over θ due to the spatial variation of δE_b , the reciprocal lifetime of a trapped electron in the presence of an applied electric field, $\frac{1}{T_t}$, is obtained:

$$\frac{1}{\tau_r} = \frac{1}{4\pi} \left(\int_0^{2\pi} d\phi \int_0^{\pi} \sin\theta d\theta \exp \left[-\frac{\delta E_b}{kT} (\theta) \right] + \int_0^{2\pi} d\phi \int_{\frac{\pi}{2}}^{\pi} \sin\theta d\theta \right)$$
(3.6)

Where it has been assumed that the electron release rate is i ndependent of the applied electric field for $\pi/2 \le \theta \le \pi$, where the potential barrier height is increased by the ele ctric field. These integrals can then be evaluated by substitution, using $t = \cos \theta$, to give an expression for the emissionen hancement due to an applied electric field:

$$\frac{\tau_{r0}}{\tau_r} = \left(\frac{1}{\alpha^2}\right) \left[\exp^{\alpha}(\alpha - 1) + 1\right] + \frac{1}{2}$$
(3.7)

Wherethereciprocallifetime in the absence of an applied electric ic field, $\frac{1}{T_{r_0}}$, is $\exp(-\frac{E}{kT})$ and α is given by:

$$\alpha = \left(\frac{q^3 \xi}{\pi \varepsilon_{si} \varepsilon_0 (kT)^2}\right)^{\frac{1}{2}}$$
(3.8)

Figure 3.19 shows the emission enhancement for silicon over the electric field strength values of interest, calculated using equation 3.7. Of the remaining two field enhanced emission processes, pure tunnelling only becomes an important contribution at electric field strengths above a few $10^7 \mathrm{Vcm}^{-1}$. Phonon assisted tunnelling is however important in the electric field strength range of interest and adds an additional component to the total field enhanced emission at e.

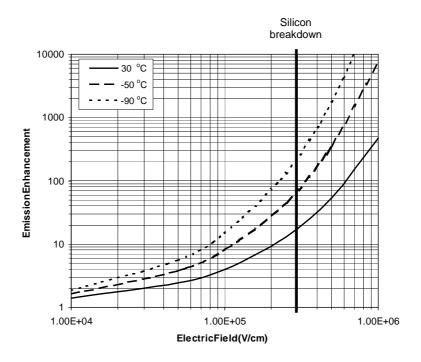


Figure 3.19 Modelled Poole-Frenkelemissionen hancement for silicon

3.4.5. TransientEffects

The highly energetic particles in a cosmic ray produce a minimu m ionisation of \sim 80electrons μ m⁻¹astheypassthroughaCCDcausingagroupofpixelsinthedev icetoappear bright,generallyonlyforasingleframebeforetheexcesscha rgeissweptaway.Usuallycosmic rayeventsaredetectedbyCCDreadoutsoftwareandremovedfromtheima geanalysis.

3.4.6. RadiationDamagePredictionTools

The main radiation effect of concern when using CCDs for spe ctral sensitivity and positional scienceisCTI.UsuallyfortheseapplicationstheCCDis operated cooled, for example at -90 and therefore the dark current component is negligible. A number of repeatable experimental studies have been carried out investigating the variation in CT I with proton flux, temperature, irradiationbias, signal charge size and readout speed. From the experimentalstudiesanumberof models have been developed that produce results comparable to t he measured CTI levels includingthosebyHollandetal.(1991),andDaleetal.(1993).Figure 3.20 showsthemodelled variation in CTI with 10 MeV proton irradiation fluence for an E2VTechnologiesCCD02device operatingat-90 °C.

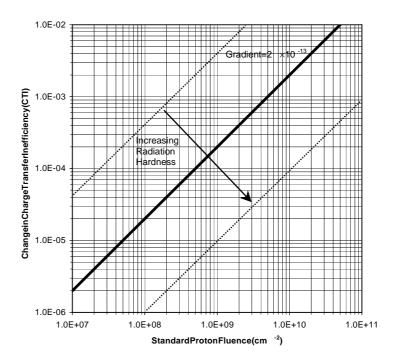


Figure 3.20 A model for CTI growth variation with 10 MeV proton irradiati on fluence for a CCD02 with an 8 μ mwide buried channel and 22 μ m² pixels operating at -90 °C (Holland et al. 1991)

3.5. Summary

This chapter has presented the various components of the space ra diation environment and etheenvironment. The described a number of computational models that can be used to simulatNIEL function has been introduced as a method of normalising proton flue nce to equivalent 10 MeV proton fluence, allowing the comparison of radiation damage results from different proton irradiation experiments. The two radiation damage mechanis ms of importance in CCDs, ionisation and displacement damage, have been described in detail, fol lowed by descriptions of the various effects radiation damage has on the operational cha racteristics of CCDs. The next sing novel low light level CCD chapter presents work carried out to assess the potential of u technology for space applications. Two devices featuring the novel technology were irradiated withprotonsandtheeffectsofradiationdamageontheoperationalc haracteristicsofthedevices wereobserved.

Chapter4:L3VisionRadiationTesting

This chapter investigates the effects of proton irradiati on on the operational characteristics of novelL3VisionCCDsinordertoassesstheirpotentialforuseinspace.Th eL3Visiontechnology is described first, followed by the experimental method employed for their radiation of two such devices. The experimental results are then presented and the observed radiation effects discussed in light of the possible use of L3Visiontechnology for space applications.

4.1. Introduction

A new CCD technology called L3Vision was developed by E2V Techno logies in 2000, that reduces the effective readout noise of a device to less than on electron, even while operating at MHz pixel rates. The device works by having an additional 'gai n' register after the readout register of the CCD in which the signal charge is multiplie d by an avalanche process before reaching the output amplifier, increasing the signal to noise (Jerram et al. 2001, Mackay et al. 2001). The effective readout noise, σ_{eff} , for again, G, is given by:

$$\sigma_{eff} = \frac{\sigma_r}{G} \tag{4.1}$$

Where σ_r is the actual readout noise of the device.

AprincipleweaknessoftheCCDasadetectoristhata fasterreadouttimeresultsinanincrease inreadoutnoise.TheL3Visiontechnologyaddressesthisproblemandprov idesdevicesthathave readoutnoisecomparabletothebestimageintensifiers.

The L3Vision devices are suited to applications where light levels are very low and therefore there is potential for their use in space based applications f or looking at faint sources. One potential space application of the L3Vision technology currently unde r consideration is the Radial Velocity Spectrometer, RVS, instrument for the planned GA IA astrometry mission. According to the current specification, the RVS instrument will becomposed of 3CCD sused to acquirespectrafromveryfaintsourcestypicallywithlessthanone signalelectronperpixelinthe spectrum. The main operational constraint on the instrument is the very small charge levels associated with the faintest stars it can observe. A possible optiontoimprovethemagnitudelimit

that can be observed by the RVS is the application of L3V isio n technology to the CCDs of the instrument.

To be a viable technology for use in the space environment it is necessary to know if the gain register of an L3Vision device is tolerant to the space rad iation environment encountered by scientific satellites, and will not be susceptible to catast rophic breakdown failure as a result of radiation damage. Brightpixels generated in the high field aval anchere gions of the gain register, as a result of radiation damage, could lead to 'white' images.

This chapter studies the effects of radiation on CCD65 devic es incorporating the L3Vision technologyandascertainstheirsuitabilityforspaceapplications. Two such devices were obtained and subjected to proton fluences representative of total missi on fluences expected to be received by typical spacecraft (Holmes-Siedle et al. 1995). This chapte r first describes the architecture of the CCD65 device before detailing the experimental methodem ployed and the result sobtained.

4.2. CCD65Structure

The CCD65 is a frame transfer device that has a standard r eadout register followed by a 'gain' registerthatmultipliesthesignalchargebeforeitiss ensedbytheoutputFET.Thedevicecanbe operated in inverted mode to suppress dark current. The inverted mode darkcurrentistypically ~200electronsperpixelpersecondat20 °C.Theimageandstoresections of the CCD are each 591 ×296 pixels, while the readout and gain registers are each 591 p ixels in length plus a few reference pixels. The device characteristics are summaris edin Table 4.1. The pixels in the gain register are larger than the other pixels in the device in order to handle the potentially larger signalchargeaftergain. Figure 4.1 shows the geometrical layout of the device.

Activeimagearea	11.52 ×8.64mm	
Imagesection	591 ×296pixels	
Storesection	591 ×296pixels	
Pixelsize: Imagesection	20×30 μm	
Storesection	13.5 ×30 μm	
Readoutregister	20×30 μm	
Gainregister	40×30 μm	
Spectralrange	400–1060nm	

Table 4.1 E2VTechnologies CCD 65 characteristics

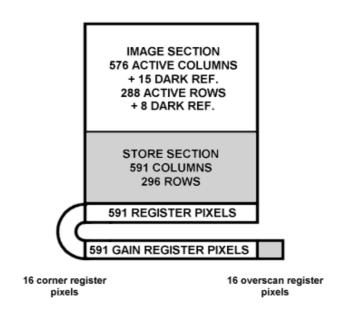


Figure 4.1 The geometrical layout of the CCD 65L3 Vision device

4.2.1. The Gain Register Avalanche Process

Thegaininthesignalasitpassesthroughthegainregiste roccur
of the pixels in the register is clocked with a much higher volta
the charge. Figure 4.2 shows a cross-section of the gain regist
potentials during charge transfer. An additional electrode held a
the high voltage electrode typically held at ~40-50 volts. The large electrode held a

oltagethanis needed to just transfer

t er electrodes and corresponding
tate 2 volts d.c. is included before
geelec tricfield present between

the high voltage electrode and the d.c. electrode causes the char ge carriers to be accelerated to a high enough velocity to generate more charge carriers through the p rocess of impaction is ation (Grove 1967).

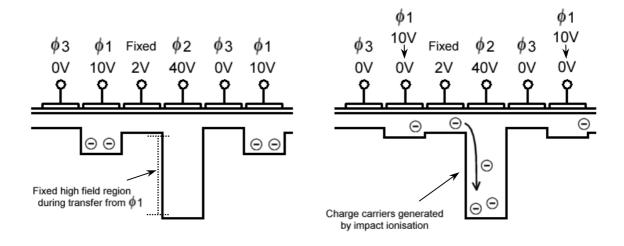


Figure 4.2 Charge transferinan L3 Vision gain register

The average gain per pixel transfer through the gain registe ris generally small, but on passing through the full 591 gain registerelements the total gain can be of G, is given by:

$$G = (1+R)^{\gamma} \tag{4.2}$$

Where R is the mean gain per transfer and γ is the number of gain elements. For the CCD65, taking R as 0.01, the gain is \sim 358. The value of R is dependent on the statistical variation in the amount of impact ionisation caused by the electric field strength between the d.c. and high voltage electrodes. By varying the bias of the high voltage electrode from a standard drive voltage of \sim 12 volts to \sim 50 volts, gain values ranging from 1 to 1000 can be obtained.

With a gain of unity the L3V ision device operates in the same w and as a standard device, with a single extra row in the readout sequence. The measured variation in gain with applied bias voltage at three different temperatures is shown in Figure 4.3. The gain is seen to increase with decreasing temperature at a given applied voltage due to the tem perature dependence of the electron ionisation rate. For a given electric field, the ionis ation rate increases with decreasing temperature as described indetail by Sze(1981).

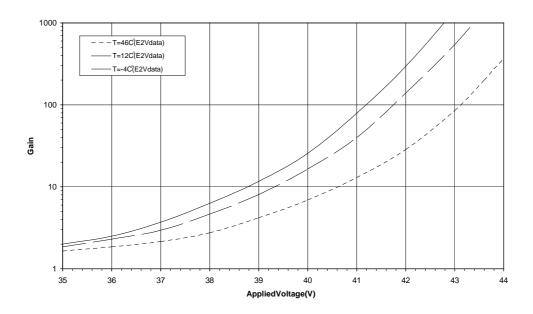


Figure 4.3 E2VTechnologies measured variation of gain with applied bias voltage for a CCD 65

The statistical variation in the gain makes it difficult t oreconstructthenumberofelectronsinthe original signal packets detected. A device using the L3Vision t echnology can only be successfully used for optical photon counting purposes when the incident photon flux is low enough to only generate a single electron in a pixel during image integration without pile-up occurring. If this is the case, the gain of the device can be s et to ~1000 to clearly discriminate singleelectroneventsfromtheoutputamplifiernoise. Figure 4.4showsthedistributionofoutput $signal size for input events of 1, 2 and 3 electrons, with a 1\,\%\,pr$ obabilityofgainperstageinthe mple Monte Carlo model. The L3Vision gain register. The data shown was generated using a si 5\sigma noise threshold is also shown, indicating that for this particul argain level, 1 and 2 electron eventsmaynotbediscerniblefromthenoisepeakaftergain.

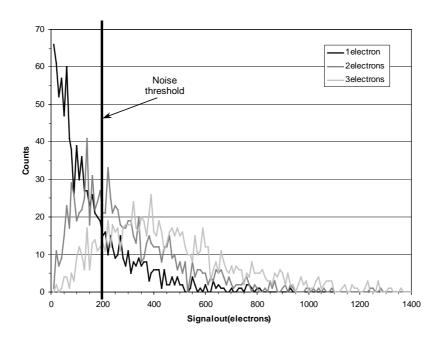


Figure 4.4 The distribution of output signal size for input events of 1, 2 and 3 el ectrons after transferthroughthe L3V ision gain register, with a 1% probability of ain pertransfer

4.3. ExperimentalMethod

4.3.1. The Accelerator Facility and Dosimetry

Irradiation of two L3Vision CCD65 devices was carried out using the cyclotron accelerator facility at Birmingham University, UK. Figure 4.5 shows a sche matic of the Birmingham beam line.

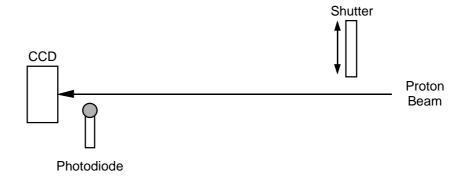


Figure 4.5 Aschematic of the Birmingham cyclotron beamline

Priortoirradiation of the devices, the uniformity of the proton beam over the target region was examined by using a photodiode in pulse counting mode. The spectrum analyser used was a Nucleus Inc. PCA-II card and software, the photodiode used was a UDT Sensors diode, part number PIN-3CD. The photodiode characteristics are summarised in Table 4.2.

Activearea	3.2mm ²	
Activethickness ^a	27 μm	
Capacitance	10pF(at10V/1kHz)	
Leakagecurrent		2nA
Risetime	15ns(50	Ω load)

^a AsdeterminedbyHolmes-Siedleetal.(1995)

Table4.2 UDTSensorsPIN-3CDphotodiodecharacteristics

The photodiode was mounted on a support arm attached to the inside face of plate which allowed the diode to be positioned on a locus passing thresholds a position ough the centre of the beam line. The flux per cm 2 reaching the photodiode in 1 minute was measured several times both in the centre of the beam and at a position 5 mm away from the centre, representative of the CCD target are ato be irradiated. The variation in beam uniformity across the target are awas measured to be $\pm 15\%$. The mean energy of the proton beam was 6.5 MeV for the irradiations carried out. An example of a typical recorded spectrum is shown in Figure 4.6.

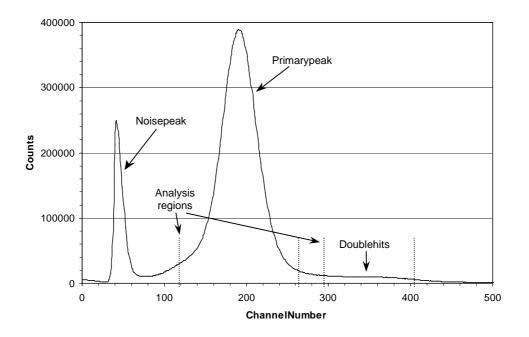


Figure 4.6 APIN-3CD photodiodepulse height spectrum

The primary ionisation peak is clearly discernible from the noise peak allowing accurate determination of the number of photons being counted in the active r egion of the photodiode. Protonsthatinteract with the diodet wice during the sames haping period, ~1 µs, are also seen in the recorded spectrum, forming a secondary 'pile-up' peak. The number of counts in the secondary peak was doubled and added to the number in the primary peak to estimate the total proton fluence. The analysis regions for each peak are indicated in Figure 4.6.

During each irradiation the photodiode was positioned $\sim 2\,\mathrm{cminfr}$ onto onto the shielded section of the target CCD and used to accurately monitor the proton fluence reaching the CCD in real time. The system live time, T_{live} , and the actual elapsed time, $T_{elapsed}$, for each irradiation were both monitored and used to account for the dead-time in the system (typically function, the final 10 MeV equivalent proton fluence received in each irradiation, F_{10MeV} , was calculated by:

$$F_{10MeV} = \left(\frac{N_{total}}{A_{diode}}\right) \left(\frac{T_{elapsed}}{T_{live}}\right) \left(\frac{NIEL(10MeV)}{NIEL(6.5MeV)}\right)$$
(4.3)

Where N_{total} is the number of counts in the primary proton peak plus two times the number of counts in the secondary peak and A_{diode} is the area of the diode. The error associated with the dosimetry of each irradiation was taken to be ~20 %, based on the be am uniformity measurements and the lack of including counts in any tertiary pe aks beyond the primary and secondary peaks in the measured photodiode pulse height spectra.

4.3.2. Irradiation of CCDs

After determination of the proton beam characteristics, the two CCDs were irradiated one after the other. Previous studies have shown that device temperature du ring irradiation does not influence the radiation damage effects observed (Holmes-Siedl e et al. 1995). The irradiations °Crequiringnocoolingequipment. In each case the target CCD werethereforecarriedoutat22 was mounted in a vacuum chamber attached to the end of the beam line. The beamlineandtarget chamberwereundervacuumduringtheirradiationstopreventlossof protonstoionisationwith air. All CCD pinswere grounded to avoid potential static dama ge. Aluminium shields were used to cover parts of the CCDs that were to be kept unirradiat ed as control areas. Figure 4.7 shows the area of each device irradiated and the 10 MeV equivalent proton do see acceptable and the 10 MeV equivhareareceived.

The whole of the readout and gain registers, and half of the image and store sections, of device 00463-10-12 were irradiated with a 10 MeV equivalent proton fluence of 5.1 \times 10 8 protons cm $^{-2}$. A 10 MeV equivalent proton fluence of 1.0 \times 10 8 protons cm $^{-2}$ was given to the left half of device 00463-10-13, with an additional dose of 2.0 \times 10 9 protons cm $^{-2}$ given to just the left half of the readout and gain registers. Figure 4.6 shows the photodiode spectrum re corded for the 1.0×10^8 protons cm $^{-2}$ irradiation of device 00463-10-13.

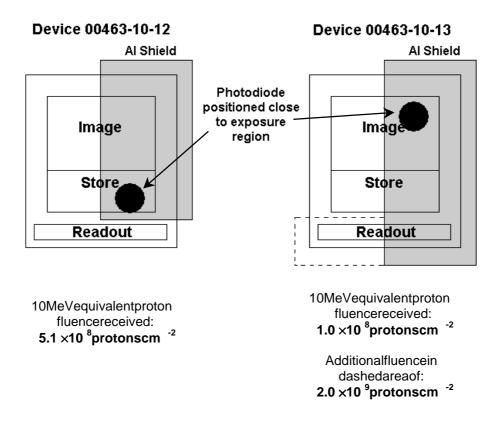


Figure 4.7 Aschematicshowing the protonir radiated areas of two L3 Vision CCD 65 dev ices and the associated 10 MeV equivalent proton doses received

4.4. ExperimentalResults

AfterirradiationbothCCDsremainedfunctionalandatatempera tureof22 °Cshowedincreased darkcurrentandbrightpixelcountscomparable tothose observed in protondoses(Ambrosietal.2002).

For device 00463-10-13 a sequencer program was used to readout only the readout and gain registerpixels of the device. The image clocks were sus pended during readout to avoid thermal leakage current from the image and store sections entering hereadout register. A series of short 3 ms row integrations were then taken. Figure 4.8 shows an accumulati on of 200 such rows, together with annotation sindicating the different device and proton expose ure regions.

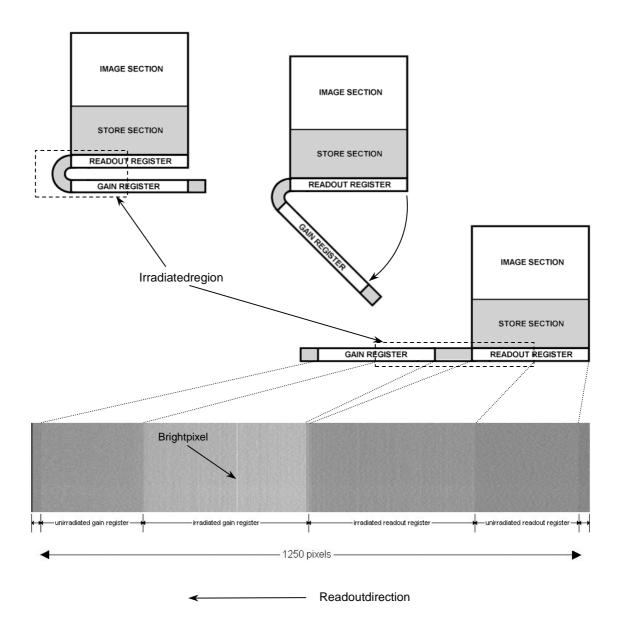


Figure 4.8 An image taken using a sequencer program that only reads out and gain registers of the device. The irradiated and unirradiat ed sections of the readout register can be seen, along with under and overscan pixels. The figure include sdiagrams of the L3V ision device to correlate the sections of the recorded image with the physical sections of the device.

Figure 4.9 shows the average of the rows in the recorded image of Figur e4.8.Thefigurehasfour sections, which are from right to left: non-irradiated readout register; irradiated readout register; irradiated gain register; non-irradiated gain register. The sl ope of the signal in the gain register, theincreaseinnumber of bright pixels and theincrease in based ark current level due to proton irradiation can all be seen in this figure. The factor of ~2 inc reaseindarkcurrentlevelbetween thegainregisterandreadoutregisterisduetothefactorof~2increase inpixelsizefromthosein the readout register compared to those in the gain register. At low applied voltage levels an indicationofprotonbeamnon-uniformity, slopes Aand BinFigure 4.9, can be seen.

Comparison of the measured postirradiation gain curves with those for the L3V ision CCD 65 as measured by E2V Technologies, Figure 4.10, show that the irradiati ons have not significantly affected the behaviour of the device.

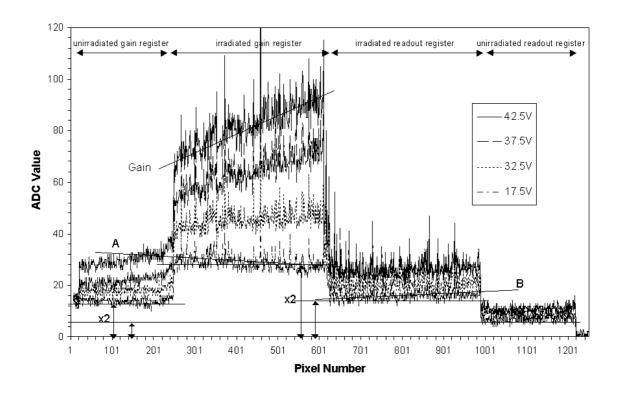


Figure 4.9 The effect of different applied voltage on the L3Vision readout and gain registers. Slopes Aand Bshowanindication of proton beam non-uniformity with lowappl iedvoltage. The gain is seen to increase sharply once the applied voltage is increased above 30 volts. The factor 2 increase indark current level between the gain register and readout register due to different pixel sizes is also indicated

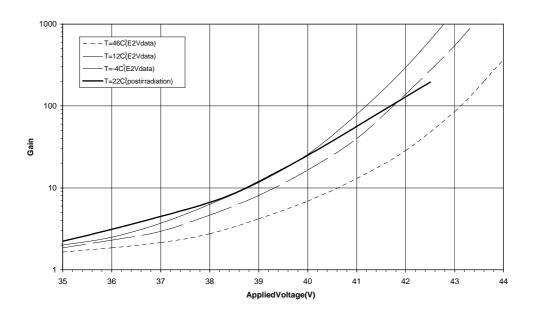


Figure 4.10 Measured variation of gain with applied bias voltage postir radiation. Gain curves as measured by E2VTechnologies for the L3V ision CCD 65 are shown for comparis on

4.5. Discussion

After irradiation with protons the L3Vision device is found to opera te normally, with the resulting change in dark current and number of bright pixels compar able to previous proton irradiation studies. The behaviour of the gain register did not change as a result of proton irradiation. Brightpixels generated in the gain register were found to increase in amplitude in the same way as the normal gain register pixels, showing no eviden ce of extraneous field enhancement effects. It is therefore assumed that the observed bright pixels generated were not located in the vicinity of a high field avalanche region.

After studying the effects of proton irradiation on two L3Vision deviproblems that would inhibit the use L3Vision technology for space b however a need to irradiate further devices in order to deduce i femiss high field regions of the gain register pixels can cause devic e failure

devices, there appear to be no ased applications. There is femission sites generated in the e failure. This study can not be

carriedoutbyirradiatingasingledevicetoahighfluenceas thiswouldresultinallthepixelsin thegainregisterbecomingbright.

In terms of area, 25 % of the gain register is comprised of th e high voltage electrode. The probabilityofobtainingabrightdefectinanavalancheregionofthegain registerafterirradiation $\times 10^{9}$ protons cm⁻², 3 bright pixels is therefore approximately 0.25. After irradiation with 2.1 were generated in the gain register of device 00463-10-13. An irra diation of 2.8 ×10 ⁹ protonscm ⁻² will therefore generate 4 bright defects in the gain regist er, one of which should lie in the avalanche region. Irradiation of 20 devices to this level will yield ~20 bright defects in the avalanche region of the device giving good stati stics on whether such a defect can $f2.1 \times 10^{9}$ protons cm⁻² as in the cause device failure. Conversely, using an irradiation level o presented study, 27 devices would need to be irradiated to generate ~ 20 bright defects in the avalancheregionofthedevice.

If the CCD schosen for the RVS instrument on GAIA use the L3 Vision technology, assuming the gain register is the same as that of the CCD 65 devices, the are may be a 1 in 4 chance of device failure when irradiating the whole gain register to a level of 2.1 \times 10 9 protons cm $^{-2}$, if a bright defect in the avalanche region does indeed cause device failure are may be a 1 in 4 chance of device of 2.1 \times 10 9 protons cm $^{-2}$, if a bright defect in the avalanche region does indeed cause device failure are meant emphasises the need for irradiation of a large number, \sim 25, L3 Vision devices.

Previous proton irradiation studies on conventional CCDs have shown tha tirradiation with the device unbiased, as in this study, induces significantly lower v oltage shifts than if the device wereoperational during their radiations. The magnitude of these voltage shifts and their effect on L3V is ion device performance also needs to be investigated in the future in radiation study.

4.6. Summary

This chapter has presented work carried out to assess the p otential for use of CCDs featuring L3Vision technology in space. Two test devices were irradiated w ith proton fluences representative of mission doses received by typical Earth or biting spacecraft. The L3Vision technology and their radiation methodology have been described follow ed by a detailed analysis of the radiation damage effects caused by the proton irradiati ons. The two devices tested were found to operate as expected afterir radiation with no significant hanges in the behaviour of the gain register, proving the L3Vision technology has potential for use in future low light level

 $space applications. The next chapter describes another series \\ different CCD type. The aim of this second study was to assess \\ irradiation on the operational characteristics of the devices.$

 $of proton irradiation studies with a \\ the effects of low energy proton$

Chapter5:TheEffectsofLowEnergyProtonsonCCD

This chapter investigates the effects of low energy proton i rradiation on the operational characteristics of E2V Technologies CCD22 devices. The reasons behind the work and the experimental method are described in detail along with a computationa 1 model that was developed to model the expected CTI changes resulting from the experimental soft proton irradiations. The experimental and modelled results are then presented and is cussed.

S

5.1. Introduction

The Chandra spacecraft demonstrated that not only X-ray photons, but s oftprotonswithenergies below 500 keV could be focused by the spacecraft's X-ray mirrors, onto the AXAF CCD al. 2000). Chandra's mirrors are ImagingSpectrometer(ACIS)(Prigozhinetal.2000,O'Dellet arranged in a Wolter Type 1 arrangement that allows the focusi ng of X-rays by shallow angle grazingincidenceontothefocalplanedetectors. Asimilarmirr ormoduledesignwasusedforthe XMM-Newton spacecraft and a study by Rasmussen et al. (1999) showed that, as for Chandra. softprotonscouldbescatteredbysingleordoublegrazinginter actions with the mirrors onto the European Photon Imaging Camera (EPIC) MOS X-ray focal plane de tectors. Figure 5.1 shows the design of a Wolter Type 1 optic and shows the path of incoming photonsastheyarefocussed bythetwomirrorsections onto the focal plane detector. The figureshows a single mirror 'shell', the actual XMM-Newton mirror module containing 58 nested mirror s hells in a coaxial and confocalarrangement.

A comparison between the space environment induced degradation of the **Chandra** instruments and the possible effect on XMM-Newton showed that the EPICMOS C CDs on XMM-Newton are susceptible to the same low energy protons that have cau seddamage to the ACIS CCDs on Chandra (Nartallo et al. 2001). The procedure for prevention of prot ondamagetotheCCDson XMM-Newton involves moving the filter wheel of each instrum entto a 'closed' position when $the radiation monitor on board detects a proton flux\,above\,athreshold$ level. The insensitivity of theradiationmonitortosoftprotonsresultsinadelayofordertensof minutesinclosingthefilter wheels, allowing soft protons to reach the detectors. In response t o these findings, a critical investigation into the effects of soft protons on EPIC MOS CC Ds was initiated to assess the impactofsoftprotonsontheoperationalcharacteristicsoftheCCDs

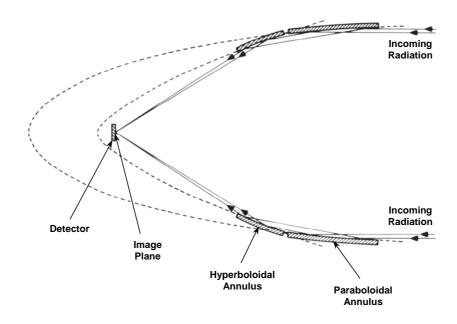


Figure 5.1 The Wolter Type 1 opticar rangement used for the mirror modules of the Chandra and XMM-Newton spacecraft

A study of the effects of soft protons was particularly im portant because soft protons have the potential for increasing CTI more than higher energy, MeV rang e, protons due to their higher scattering cross-section. Soft protons therefore penetrate only a short distance into a CCD, depositing most of their energy inthevicinity of the buried channel, where charge is transported.

Two CCD22 devices, the same as those used in the EPIC MOS cam eras of the XMM-Newton satellite (Turner et al. 2001), were taken to the University of Tübingen to be irradiated with protons using a 3.5 MeV Van de Graaff accelerator facility. The CCD22 structure is presented below, followed by detailed descriptions of the irradiation methodolog y and data analysis. A Monte Carlo model developed to simulate the observed CTI changes that resulted from the protonirradiationsisalsopresented.

5.2. CCD22Structure

The CCD 22 device is a frontilluminated three-phase frame transfer device manufactured by E2V Technologies (Shortetal. 1998). The CCD 22 uses high resistivit ysilicon and an open electrode structure to obtain good quantum efficiency between 0.2 keV and 10 keV. The image section of the CCD consists of 600 \times 600 pixels of 40 μ ms quare with an additional 2 charge injection rows. The store section consists of 600 \times 602 pixels, each measuring 39 μ m \times 12 μ m. The device characteristics are summarised in Table 5.1. Each of the two X MM-Newton EPIC MOS focal plane camerasis comprised of 7CCD 22 devices arranged as shown in Figure 5.2.

Activeimagearea	24 ×24mm	
Imagesection	600 ×600 pixels	
g, ,:	500 500 1	
Storesection	600 ×602 pixels	
	40 40	
Pixelsize: Imagesection	40×40 μm	
G:	20 . 12	
Storesection	39×12 μm	
Dan Janeton Satan	20 × 12 · · · ·	
Readoutregister	39×12 μm	
Spactralranga	0.1–15keV	
Spectralrange	0.1–13Ke v	

Table 5.1 E2VT echnologies CCD 22 characteristics



Figure 5.2 The XMM-Newton EPICMOS focal plane camera CCD arrangement

5.3. ExperimentalMethod

5.3.1. The Accelerator Facility and Proton Damage Be

The 3.5 MeV Van de Graaff accelerator at the Eberhard-Karls has a beamline dedicated to soft proton damage tests and was c effect of soft proton damage on the pn-CCD sused in the EPIC progra Figure 5.3 shows a schematic diagram of the experimental set irradiations.

amLine

-Universität Tübingen, Germany, ommissioned for evaluating the m(Kendziorraetal. 2000). up used for the CCD22

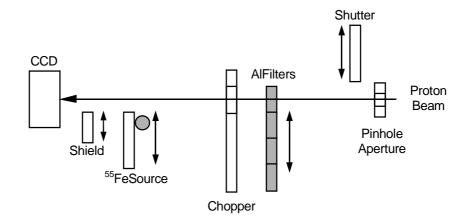


Figure 5.3 Aschematic of the Tübingen proton damage beamline

Amonoenergetic 900 keV nano-ampproton beam with a flux of ~1.0 $\times 10^{-11}$ protons cm $^{-2}$ s $^{-1}$ was reduced to ~10 4 protons cm $^{-2}$ s $^{-1}$ by a copper pinhole aperture of 1.5 mm diameter. A luminium foil filters of 10 $\,\mu$ m, 12 $\,\mu$ m, 13 $\,\mu$ m and 14 $\,\mu$ m thickness on a sliding holder were used to attenuate and broaden the spectral distribution of the beam. The mean energy of protons transmitted through each foilis given in Table 5.2 (Clau $\,\beta$ 2000). A rotating beam chopper with a 0.3 mm wide slit reduced the flux by a further factor of ~10 $\,^3$. For calibration purposes a $\,^{55}$ Fe source could be moved in and out of the field of view of the CCD. A shutter was available to shield the CCD from the proton beam when not carrying out an irradiation.

AlFoilThickness(μm)	Meanenergyoftransmittedprotonspectrum(keV)
14	10
13	70
12	170
10	330

Table5.2 MeanprotonenergytransmittedthroughdifferentAlfoilthicknesses(Cl auβ2000)

The final component of the beam line was a movable shield that could be positioned to cover the top or bottom half of the CCD by turning a dial on the outside of the prevented the need to open the beam line and break the vacuum when changing the shield position to irradiate different sections of a CCD.

Protonspectrameasured byapn-CCDusing 12 μ mand 13 μ mAlfoilsareshown in Figure 5.4 (Clau β 2000).

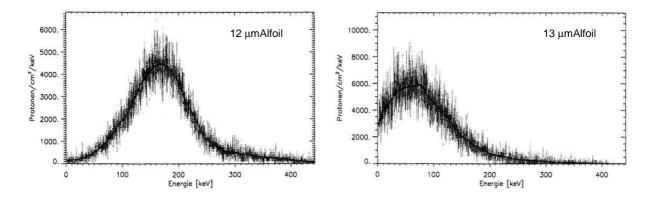


Figure 5.4 Protonspectrameasured by apn-CCD using 12 μm and 13 μm Alfoils (Clau β2000)

5.3.2. IrradiationandCalibrationofCCDs

Two EPIC CCDs were selected for irradiation. In each case the target CCD was fixed within a cryostat chamber bolted to the end of the beam line and cooled t o -100 °C, the operational temperature of the devices on XMM-Newton. The CCD was located approxim ately200mmfrom the end of the beam line with an aluminium shield placed in front o f the CCD store section to prevent X-rays or protons falling on it and causing CTI changes in the serial register. Although the CCDs selected for these tests were characterised in t erms of CTI and response to various X-rayenergies between 200 eV and 10 keV prior to irradiation w ith soft protons, the use of the movable shield in the beam line allowed certain areas of each CCD to be kept undamaged, providing a control for the damaged sections. The beam line and c ryostat containing the target CCD we reunder vacuum duringirra diation to prevent loss of protonstoionis at ionwithair.

Priortoeachirradiation, the position of the proton beamwas me asuredtoensureanevenspread of protons across the area to be irradiated. This was achieved byirradiatingtheCCDoperatingin photoncounting mode for ~1 s with a very low flux rate, using the 14 µmaluminium foil. The used to deduce where the CCDobserved distribution of protons in the resulting CCD image wasshouldbemovedtoobtainthedesireduniformity. The 14 µmfoilandveryshortirradiationtime were used for the beam positioning to prevent any damage to the C CD. The mean energy of protons transmitted through the 14 µm foil was 10 keV. This energy is low enough to be attenuated by 0.3 µmof silicon preventing any significant amount of energy being deposi tedin theburiedchannelofthedevice.

Before an irradiation, the target CCD was exposed to a short burst of protons in order to determine the protonflux, P_{flux} , passing through the aluminium foil being used:

$$P_{flux} = \frac{N_p}{T_f A_{ROI}} \tag{5.1}$$

Where N_p is the number of protons detected in an area of interestinasing lef time, and A_{ROI} is the size of the region of interest. The exposure time, T_d , for each section of the CCD to receive the required proton dose, η , could then be calculated:

$$T_d = \frac{\eta}{P_{flux}} \tag{5.2}$$

The total fluence received by each section of the two CCDs i shown in Figure 5.5. The white panels in the figure refer to their radiated areas of the CCDs. The mean proton energy transmitted through each foil filter is also given in each panel. Each irradiation was preceded and followed by a calibration check with the street of the two CCDs is shown in Figure 5.5. The white mean proton energy transmitted through each foil filter is also given in each panel. Each irradiation was preceded and followed by a calibration check with the street of the two CCDs is shown in Figure 5.5. The white mean proton energy transmitted through each foil filter is a large fragment of the two CCDs. The mean proton energy transmitted through each foil filter is a large fragment of the two CCDs. The mean proton energy transmitted through each foil filter is a large fragment of the two CCDs. The mean proton energy transmitted through each foil filter is a large fragment of the two CCDs. The mean proton energy transmitted through each foil filter is a large fragment of the two CCDs is shown in Figure 5.5. The white mean proton energy transmitted through each foil filter is a large fragment of the two CCDs is shown in Figure 5.5. The white mean proton energy transmitted through each foil filter is a large fragment of the two CCDs is shown in Figure 5.5. The white mean proton energy transmitted through each fragment of the two CCDs is shown in Figure 5.5. The white mean proton energy transmitted through each fragment of the two CCDs is shown in Figure 5.5. The white mean proton energy transmitted through each fragment of the two CCDs is shown in Figure 5.5. The white mean proton energy transmitted through each fragment of the two CCDs is shown in Figure 5.5. The white mean proton energy transmitted through each fragment of the two CCDs is shown in Figure 5.5. The white mean proton energy transmitted through each fragment of the two CCDs is shown in Figure 5.5. The white mean proton energy transmitted through each fragment of the two CCDs

AttheendofeachdayoftestingtheCCDswerewarmedtoro omtemperatureandmaintainedat thistemperatureovernight. Anyannealing effects were observe deach morning when the devices were again cooled to 100 °C and calibrated with the SF Fesource.

Estimates from solar event spectral measurements taken by the EPIC pn-CCD camera on XMM-Newton (for protons between 100 keV and 200 keV) indicate that the EPIC MOS CCDs may have already received a soft proton dose of the order of 10⁵ protons cm -² in the worst case (Kendziorra et al. 2000). In this experiment, total doses exceeded 10 ⁶ protons cm -², a value representative of the total dose the EPIC MOS devices ar eexpected to receive over 10 years of operation.

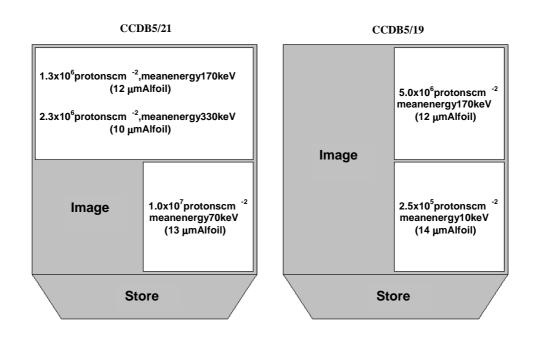


Figure 5.5 Total doses given to each section of their radiated CCDs

5.3.3. RecordedProtonSpectra

The proton spectra obtained with the two CCD22 devices using the f our available aluminium foils are shown in Figure 5.6. In each case, the count rate at the C CDhadtobelowenoughto avoidpile-upduringthe 5.4s frametime of the CCD. To avoid ADC saturation, the system was controlled by adjustment of the charge integration time. The complet e proton spectrum through each aluminium foil could not be measured by the CCD due to limit ations in pixel integration time and gain reduction. These limitations can be seen in the pl ots of Figure 5.6, where the $\mu maluminium foil is 480 keV and through the 12$ highestenergy measured through the 10 μm, 13 μmand14 μmfoilsitis182keV.

The double peak in panel Dof Figure 5.6 is not are a leffect and is caused by the saturation of the analogue to digital converter. The peak at 200 keV is caused by mul central pixel is saturated and charge has spread into adjacent pixels. The digital value of this pixel is therefore not representative of the total energy deposited by the proton in the pixel. At proton energies above 200 keV the penetration depth is higher in silicon and most of the events will be spread between several pixels as a result of charge being deposited in the field free region.

Incomparing the measured CCD22 proton spectra through the 12 $$\mu m$ and 13 μm Al foils with those measured by the pr-CCD (Figure 5.4), an additional large lowen ergy component is seen in the CCD22 spectra. This difference is the result of charge loss effects observed in the CCD22 device where electrons generated near the surface of the device ebecome redistributed by tapping sites at the oxide interface. The amount of charge loss is mor e prevalent at lower temperatures and is a strong function of decreasing incident particle energy (Shortetal. 2002) .$

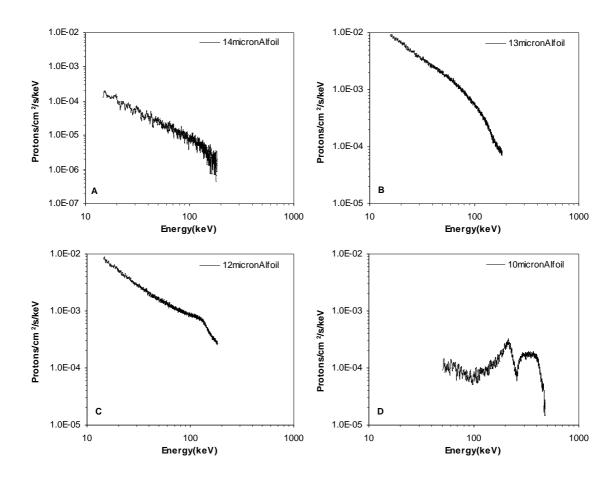


Figure 5.6 Proton spectra measured with EPIC MOS CCDs after irradiation through four differentaluminiumfoilthicknesses

5.4. Computational Model

PredictingtheCTIchangeintheCCDsirradiatedwithlowenergyprot onswasnotpossibleusing the standard Non-Ionising Energy Loss, 'NIEL', method of obtaining the 10 MeV equivalent proton dose. NIEL displacement damages cales with dose as the proton dose and the pronenergydecreases(Daleet al. 1993). Below 1 MeV however, NIEL ceases to be an effective method of predicting CTI change as a function of proton dose. This is as a result of low er energy protons physically stoppinginthevicinityoftheCCDburiedchannel,depositingtheirmaximum energyintheplace where it will cause the most damage. NIEL also does not take the geometry of the CCD into account. Another method of modelling the CTI change was required. The solutionwastousethe Stopping Range of Ions in Matter (SRIM) program (Ziegler et a 1.1985) to model the effect of lowenergyprotonsinarepresentativeCCDstructure.

5.4.1. ModellingExpectedCCDDamageUsingSRIM

The SRIM program was first used to model 1000 protons interacting w ith a representative CCD22 structure at a number of input energies between 0.1 MeV a nd 100 MeV. Due to the limitations of the SRIM program and the available knowledge of the layered structure of the CCD22, the buried channel was taken to be 0.4 μ m wide at a depth of 1.57 μ m below the hypothetical CCD surface (Holland 1994, Ambrosi et al. 2002). The input parameters of the modelaregiveninTable5.3.

Layer	Material	Depth(μm)	Thickness (µm)	Density (g/cm³)
OxideandVAPOX	SiO_2	0.000-0.500	0.500	2.27
Electrode	Si	0.500-1.000	0.500	2.33
NitridePassivation	Si_3N_4	1.000-1.085	0.085	3.44
OxideProtection	SiO_2	1.085-1.170	0.085	2.27
ActiveRegion	Si	1.170-2.670 ^a	1.500	2.33

^aTheburiedchanneliswithinthisregionatadepthof1.57 μm

Table5.3 SRIMMonteCarlomodelinputparameters

The SRIM output data allowed calculation of the percentage of a given input proton's energy deposited into the chosen buried channel volume. The output of this simul ationandthefittothe dataareshowninFigure 5.7. The fit consists of a Gaussian, representing thestandarddistribution of energy deposited by protons actually stopping within the CCD buri edchannel volume, and a split power law representing the NIEL function. The figure shows that protons below 140 keV will not penetrate far enough into the CCD 22 structure to reachtheburiedchannel of the CCD, and therefore they will not contribute to an increase in CTI. The largest amount of energy is depositedintheCCDburiedchannelwhentheincomingprotonhasane nergyof223keVatthe surfaceoftheCCD.Figure 5.8 shows data from four of the many SRI Msimulationsusedinthe Monte Carlo model. The four panels of the figure show the ion is ationtracks of incident protons, withenergies of 100, 200, 300 and 1000 keV respectively, interacting w iththesimulatedCCD22 structure. The position of the buried channel is indicated in eac h panel showing that incident protons of ~200 keV will deposit most of their energy in the vic inity of the buried channel volume.Incidentprotonsofenergy>1MeVpassfarbeyondtheburiedchannel beforedepositing themajority of their energy, the resulting displacement damages caling withtheNIELfunction.

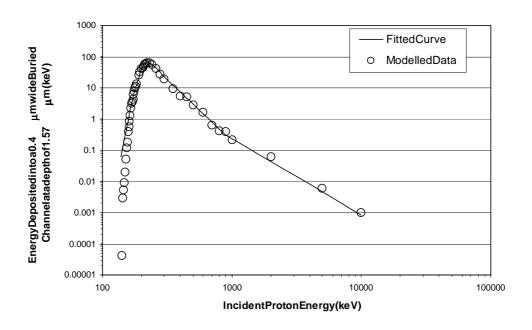


Figure 5.7 The amount of energy deposited into a 0.4 μm wide buried channel at a depth of 1.57 μmfromthesurfaceofarepresentative CCD22 structure as a function of interacting proton energy

If the depth of the CCD 22 buried channel is in fact deeper than the mode in Figure 5.7 becomes shifted to the right, a converse shift occurring shallower. If the buried channel is narrower, while still fixed remains in the same place, but the fraction of energy deposite denotes but the deposite denergy fraction increases if the channel that the radiation hardness of buried channel CCDs scale channel, as shown by Wattsetal. (1994).

e lleddepth,thenthepeak ifthedepthofthechannelis at the modelled depth, the peak dateachinput energy decreases. nelis wider. This emphasises the s with the width of the buried

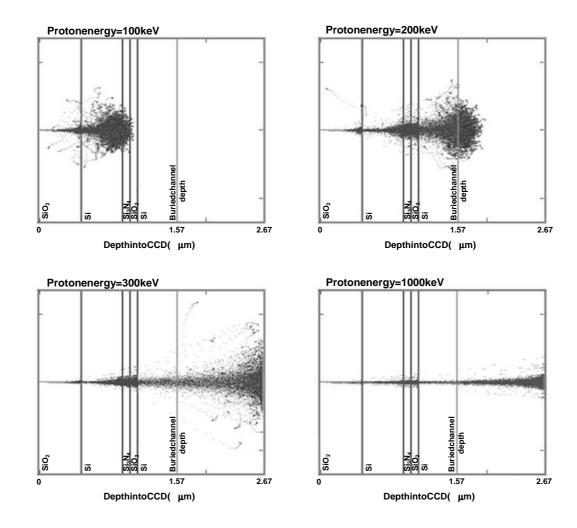


Figure 5.8 The ionisation depth of protons interacting with a representative CCD22 structure overthecharge transfer path. The buried channel depth is indic ated in each panel, showing that protons of ~200 keV deposit the most energy into the buried channel volume

5.4.2. ModellingCTI

The SRIM model was used in conjunction with the experimentally mea sured energy spectra to calculate the total amount of energy, E_{bc} , in keV deposited within the specified buried channel volume by the proton beam, given by:

$$E_{bc} = \sum_{1}^{i} \left(N_{bin} E_{p} \frac{\xi}{100} \right) \tag{5.3}$$

Where *i* is the total number of energy bins in the spectrum, N_{bin} is the number of counts in each energy bin, E_p is the input proton energy (in keV) associated with the energy y bin and ξ is the percentage of the input energy deposited in the buried channel, obtained from the SRIMm odel.

For each of the CCD22 irradiations E_{bc} was calculated and then used to deduce the 10 MeV equivalent protonfluence, F_{I0MeV} , deposited in the buried channel:

$$F_{10MeV} = \frac{E_{bc} A_{irr}}{100 \xi_{10MeV}} \tag{5.4}$$

Where A_{irr} is the area of the CCD irradiated and ξ_{10MeV} is the value obtained from the SRIM modelforaninputenergy of 10MeV and is 8.57 ×10⁻⁶%.

The corresponding parallel CTI change was then deduced using:

$$CTI = XF_{10MeV} (5.5)$$

Where X is the rate of change of CTI with proton dose for an EPIC MOS CCD operating at -100 °C. In this case $X=1.62 \times 10^{-14}$ and was determined experimentally in a study by Ambrosi et al. (2002), wherean EPIC MOSCCD was exposed to increasing doses of 10 MeV protons and the CTI was measured as a function of progressive amounts of da mage. Linear relationships between CTI change and proton dose have also been reported by Wattset al. (1994).

5.5. ExperimentalResults

Two CCDs were irradiated with varying proton energy distributi ons. The CTI for each device was measured prior to each irradiation and for device B5/21 this i s shown in panel A of Figure 5.9. Panel B shows the change in CTI of the same device afterirradiation with a proton spectrumpassingthroughthe13 µmaluminiumfoil.PanelCshowsamoredramaticCTIchange observed when the device was exposed to a spectrum of protons thatcould inflict more damage to the buried channel, while panel D confirms that as the number of protons that can contribute damageintheburiedchannelincreases, the CTI increases. Nonew brightpixels were present in °C. thetwodevicesafterirradiation, operating at-100

The 55 Fe calibration source illuminating the image section of the CCD was used to determine changes in the resolution of the K α peak at 5898 eV after irradiation through the 12 μ m aluminium foil as a function of proton dose. The intrinsic resolut ion prior to damage was measured to be ~ 150 eV. The increase in CTI degraded the resolut ion to ~ 170 eV, a 13 % reduction.

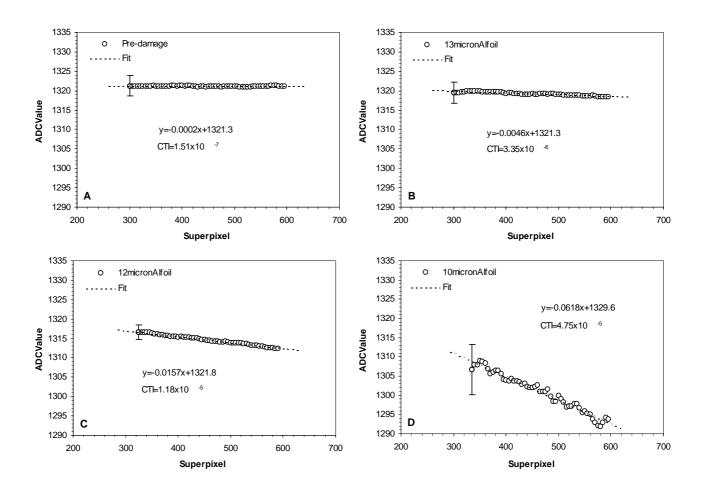


Figure 5.9 The four panels depict the measured CTI before and afterprotonirradiation of device B5/21 through different thickness a luminium foils. The error barine ach panel is the same for each data point in that panel. Pixels have been binned in five stocreate 'S uper Pixels'

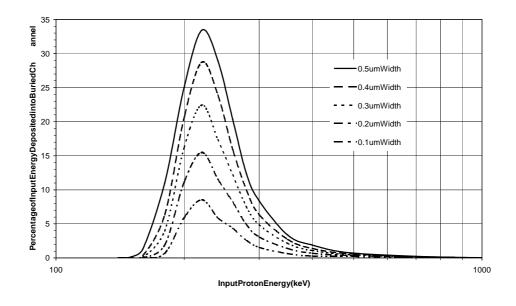
5.5.1. ComparisonofModelandExperiment

The experimental and modelled CTI results for their radiated devices a recompared in Table 5.4.

CCD Ti	AlFoil	MeanProton	ExperimentalCTI	ModelledCTI	<i>Ratio</i> (±25%)
	Thickness(µm)	Energy(keV)	Change(±5%)	Change(±20%)	(Experimental/Modelled)
B5/21	13	70	3.35 ×10 ⁻⁶	2.55 ×10 ⁻⁶	1.3
B5/21	12	170	1.18 ×10 ⁻⁵	6.79 ×10 ⁻⁶	1.7
B5/21	10	330	4.75 ×10 ⁻⁵	6.13 ×10 ⁻⁶	7.7
B5/19	14	10	9.20 ×10 ⁻⁷	5.34 ×10 ⁻⁸	17.2
B5/19	12	170	5.25 ×10 ⁻⁵	3.32×10 ⁻⁶	15.8

Table 5.4 Comparison of experimental and modelled CTI changes

The differences between modelled and experimental CTI values we reasexpected. The modelled values are a lower limit for the CTI owing to the fact that the input spectra are incomplete, for examplethespectrum associated with the 12 µmfoil,stopsat182keV.Thefullspectrawillhave ahigher proton energy component traversing the CCD, depositing a small amount of additional energy in the buried channel and this would account for part of the di fference. The difference between modelled and experimental CTI values may also be explained if the representative CCD22 structure and the location and width of the CCD buried channe lare slightly different to theparametersused in the model. Figure 5.10 shows how changing them odelledburiedchannel width, or depth below the CCD surface, affects the percentage of the input proton's energy deposited into the buried channel volume. Device B5/19 was taken from adifferentsiliconwafer thanthat of B5/21 most likely resulting in the buried channel of one device being wider or in a slightly different location to that of the other (Gardiner 2003). This explains why the experimental to modelled ratios for device B5/19 are higher th an those for device B5/21. The µmfoilirradiationofdeviceB5/19isdueto increaseinexperimentaltomodelledratioforthe14 the 'doublepeak' occurring in the input spectrum to the SRIM mode lcausedbysaturationofthe ADC.



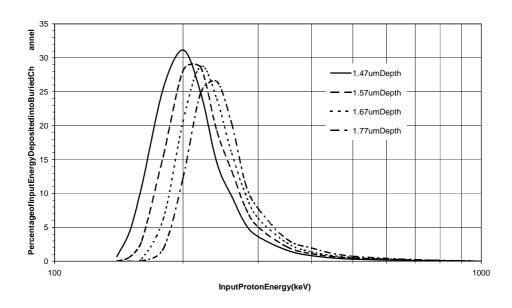


Figure 5.10 The effect of varying buried channel width and depth below the C CD surface on the amount of energy deposited in the buried channel

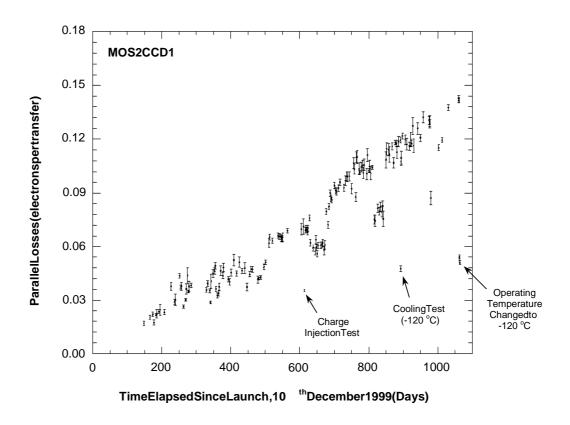
5.6. Discussion

SoftprotonsofafewhundredkeVcanrapidlydamagethecharge transfercapabilitiesofCCD22 devicesduetothehighercrosssections associated with prot onsofenergies below 900 keV. This is emphasised by the Monte Carlo model developed for this study, whi amount of damage to the buried channel is associated with the hig deposited withinit. For an input proton energy of ~220 keV most of the restinthe CCD buried channel, causing maximum damage. As the input proton energy deposited in the buried channel decreases and hence larger doses are required to produce the same observed amount of damage.

The results of on-orbit CTI measurements for both MOS cameras onboard XMM-Newton over the first 1070 days of the mission have now been documented. All 7 CCD s of both the MOS 1 and MOS 2 cameras show a steady increase in CTI over the curr ent duration of the mission. Figure 5.11 shows the gradual increase in parallel transfer lo sses for Mn-K \(\alpha X\)-rays, for CCD1 of MOS2. The general 'slope' of the data is due to displacement damage caused by protons in theradiationbelts.XMM-NewtonpassesthroughtheEarth's radiati onbeltsduringeach48hour revolution, each time encountering some high energy protons that hav e enough energy to penetrate the shielding around the detectors and cause displace ment damage in the CCDs. The larger 'steps' in the data are associated with periods of in creased solar activity where displacement damage is caused by high energy solar protons. Figure 5.11 also indicates parallel loss values recorded during charge injection and cooling tests. T he charge injection test was carried out in revolution 330 and showed that the technique could reduce the CTI by $\sim 50 \%$ (Abbey 2002). The use of charge injection did not restore the CTI t o the pre-launch value and also introduced 10 – 200 additional bright pixels into the CCD fra mes recorded when charge injection was used. The cooling test in revolution 448 was used to inve stigatethechangeinCTI °C resultingfromadecrease of 20 °Cintheoperatingtemperature of the EPICCCDs from -100 to-120 °C(Abbeyetal.2002). This technique reduced the CTI by slightly more than 50% and after revolution 533 was implemented permanently, indicated by the la st two measurements in Figure 5.11.

The average CTI values associated with MOS 1 and MOS 2 at da y 580 were 1.3 \times 10 ⁻⁵ and 1.7 \times 10 ⁻⁵ respectively (Bennie 2001). Estimates made by Kendziorra et al. (2000) from solar event spectrum measurements made with the pn-CCD camera at tha t time, showed the MOS cameras should have received do ses of ~10 ⁻⁵ protons cm ⁻², where the proton energy was estimated

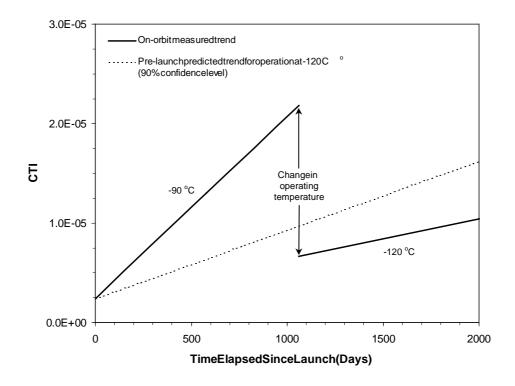
to be between $100 \, \text{keV}$ and $200 \, \text{keV}$. By folding a value between $1 \, \times 10^{\,5}$ protons cm $^{-2}$ and $2 \times 10^{\,5}$ protons cm $^{-2}$ through the SRIM model, the equivalent $10 \, \text{MeV}$ fluence can be calculated and hence the expected CTI, which in this case lies between 7.3 $\times 10^{\,-6}$ and 1.5 $\times 10^{\,-5}$. The upper limit of this range is within the average CTI changes for the two MOS cameras, quoted by Bennie (2001).



 $\label{eq:continuous} \textbf{Figure 5.11} \ \ \textbf{On-orbit measurements of the Mn-K} \quad \alpha parallel transfer losses of MOS 2 CCD 1 as a function of time$

Figure 5.12 shows the average CTI trend over the duration of the m ission for the 7 CCDs of MOS 2. The on-orbit trend is extrapolated from day 1066 after the ope rational temperature was reduced to -120 °C using the CTI value obtained for the cooling test in revoluti on 448 and the CTI values obtained since the change in operational temperature. For com parison, the dashed line

of the figure shows the 90 % confidence level CTI trend that wa s predicted before launch for °C. This predicted trend was based on CCD22 irradiation operation of the MOS CCDs at -120 tests carried out before the launch of XMM-Newton that concluded t he CTI after 7 years of operationshouldbe~2 ×10⁻⁵. The measured trend at -120 °Cisbelowthelevelpredictedbefore launch, indicating that soft protons only account for a minor frac tion of the observed CTI increase, <20%, the MOSCCD sbeing subjected to a predominantly hardprotonspectrum. This low level of soft protons indicates that the operation of the spac ecraft with regard to preventing soft protons reaching the CCD detectors is optimal and no operational changes need to be made. Asreported by Kendziorra et al. (2000), the EPIC pn-CCD detector onXMM-Newtonwasused to measure the proton spectra of solar events and the results show ed typical fluxes of 0.2 protons cm⁻² s⁻¹ between 100 keV and 200 keV. Given these measurements, it would take 2.5×10^{6} s (~29 days) of continuous staring at such events to sustain the total changes in CTI giveninTable5.4.



 $\textbf{Figure 5.12} \ \, \textbf{The pre-launch predicted and on-orbit measured Mn-K} \qquad \alpha parallel \ \, \textbf{CTI change over time for the CCDs of MOS 2}$

5.7. Summary

This chapter has described an investigation into the effects of low energy protons on CCD22 devices, the same devices as those used in the EPIC MOS detect ors of the XMM-Newton spacecraft. The CCD 22 structure and irradiation methodology have been considered as the considered control of the considered control of the control of thnpresentedfollowedbya detaileddiscussionoftheradiationdamageinducedCTIchanges caused by their radiations. The development of a computational model to simulate the CTI changesthatresultedfromtheproton irradiationshasalsobeenpresentedandshowntoproduceusefulresult s. The soft proton damage component to the on-orbit CTI measurement staken from the EPICMOSdeviceswasfoundtobe small, the current operation of the spacecraft during solar events being sufficient to keep the observed CTI change comparable to that expected pre-launch. The next chapter presents a detailed investigation of a specific radiation induced phenomenon, that of fluctuating bright pixels. The irradiation of two CCD47-20 devices is described, foll owed by an in-depth analysis of the collected data and a discussion of several models put f orward to explain the mechanism behindfluctuatingpixels.

Chapter6:RandomTelegraphSignals

This chapter investigates fluctuating pixels resulting from proton irradiation of two E2V Technologies CCD47-20 devices. The device structure is describe d first followed by a description of the experimental setup and their radiations carried out. Apreliminary study of one device is then presented followed by a detailed investigation of fluctuating pixels in the second device. The characteristics of flickering pixels are discus sed in detail and the proposed models explaining the mechanism behind the phenomenon are viewed in light of the collection.

6.1. Introduction

The generation of bright pixels as a result of irradiation of a CCD has been discussed in the preceeding chapters of this thesis. This chapter deals with a specific type of radiation-induced brightpixel;thoseobservedtohaveafluctuatingchargelevel. The apparentrandomnatureofthe fluctuation period has resulted in such pixels being called 'flicke ring pixels' which are said to exhibit 'Random Telegraph Signal' (RTS) behaviour. The term RTS has also been applied to 'flicker', or '1/f' noise, as described in Chapter 2 (Kandiah 1985, Kandiah et al. 1989). Flicker noise, however results from electron and hole emission and captur efrominterfacetrapsadjacent to the channel region of any CCD FETs, while the RTS phenomena unde rstudyinthischapter are shown to result from bulk traps, showing well defined time const ants and characteristics independent of the surface conditions of the CCD. Little study has been made of the RTS phenomenon, the main reference sources for information being the pub lishedpapersbyHopkins and Hopkinson (1993, 1995) whose investigation of RTS was initiated as a resu **ltofotherauthors** reportingCCDpixelsexhibitingfluctuatingdarkcurrentlevel s(Srouretal. 1986, Marshalletal. 1989).

The period of amplitude fluctuation is shown later in this chapter to be proportional to the temperature of the CCD. As the operational temperature of a device is reduced, the mean time constants for the low and high amplitudes of the fluctuation are inc reased. CCDs used in X-ray applications are usually cooled to around -100 ^oC where the mean time constants are of order several days and will not cause significant concern in the coll ection of data. RTS pixels are however still observed at such low temperatures, for example 5 % of background events in the MOS2camera of XMM-Newton, operating at -120 °C, are the result of flickering pixels in 5 of the 7 CCDs (Ballet 2003). At temperatures above -20 °C the time constants become of order hoursandstarttobecomemoreofaproblemindataanalysis.RTSha salreadycausedsignificant problemsfortheopticalCCDdetectorsoftheGOMOSinstrumentonthe ENVISATsatelliteand may also become more significant in future X-ray missions wher e the trend is for warmer operation CCDs, for example the Demonstration of a Compact Imaging X-ray Spectrometer (D-CIXS) instrument on the SMART1 mission to observe the Moon and i ts subsequent developmentfortheBepiColombomissiontoMercury.

The mechanism behind RTS is still not well understood and the wor was initiated to provide information to improve the current propo sed models of RTS. This chapter first describes the CCD47-20 devices used for the study and the proton irradiations carried out before describing the techniques used to characteris e the resulting pixels exhibiting RTSbehaviour.

6.2. CCD47-20Structure

The E2V Technologies CCD47-20 is a front illuminated frame trans for device that can be operated in inverted mode to suppress dark current. The image and st ore sections of the CCD each contain 1024 ×1024 pixels of 13 µm square. The device characteristics are summarised in Table 6.1.

Activeimagearea	13.3 ×13.3mm
Imagesection	1024×1024pixels
Storesection	1024×1024pixels
Pixelsize: Imagesection	13.0×13.0 μm
Storesection	13.0×13.0 μm
Readoutregister	13.0×13.0 μm
Epitaxialsiliconthickness	20 μm
Resistivity	20–30 Ωcm
Spectralrange	400–1100nm

Table6.1 E2VTechnologiesCCD47-20characteristics

6.3. IrradiationofCCDs

Irradiation of one CCD47-20, device number 9211-5-3, was carried out using the Birmingham University cyclotron facility described in Chapter 4. The same dos imetry techniques were again used, the error associated with the dosimetry of each irradia tion taken to be ~20 %. Two irradiations were carried out with CCD 9211-5-3 at room temperature .A6.5MeV proton beam ×10 8 protonscm -2 toonethirdofthe wasusedtogivea 10 MeV equivalent proton fluence of 1.5 CCD. The rest of the CCD was covered with an aluminium shield to prevent the protons damagingthatpartofthedevice. It should be noted that the store secti onoftheCCD47-20hasits own aluminium shield, although this is not thick enough, ~1 μm, to stop the protons passing throughit.

AsecondirradiationwascarriedoutwithtwothirdsoftheC CD shielded with a luminium while therestofthedevicewasirradiatedthrough 100 µmofcopperfoil. The copperhad the effect of reducing the mean energy of the proton beam to 2.0 MeV. The same flux ofprotonswasgivento the CCD as for the 6.5 MeV irradiation. The 10 MeV equivalent proton for the following the contraction of the contraction ofluencegiveninthiscase was 3.6 $\times 10^{-8}$ protons cm ⁻². For the second irradiation the photodiode was also covered with 100 µmofcopperinordertomeasurethesameprotonfluxandmeanenerg yasthatreachingthe CCD. The central part of the CCD remained unir radiated as acontrolarea. The shielding regime and 10 MeV equivalent proton dose received by each area of device 9211-5-3 are shown in Figure 6.1. The exposure time for each irradiation was ~80 seconds.

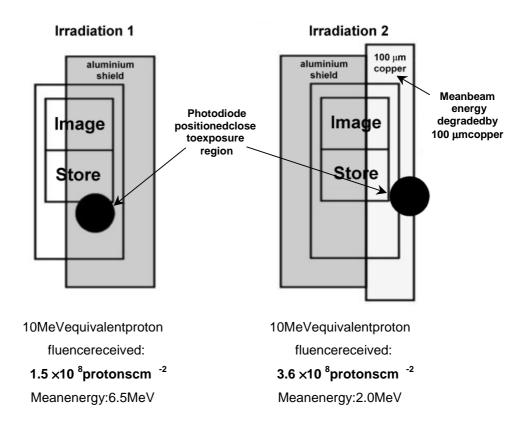


Figure 6.1 Aschematic showing the proton irradiated areas of device num ber 9211-5-3 and the associated 10 MeV equivalent proton doses received

A second CCD47-20, device number 9211-4-4, was irradiated using the dedic ated 10 MeV proton damage beam line at the tandem Van de Graaff accelerat or facility run by AEA TechnologiesinHarwell,UK.Figure6.2showsaschematicoftheHarwellb eamline.

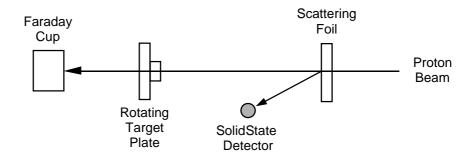


Figure 6.2 Aschematic of the Harwelltandem Van de Graaffbeamline

Before irradiation, an even distribution of protons across the t arget area was achieved and verified by use of a series of scattering foils. By rotati ng the sample plate out of the beam, the charge accumulated in the Faraday cup at the end of the beam line and the number of scattered particles in the solid state detector were used to determine t he number of particles reaching the target area. This calibration was carried out by Harwell s taff and was used to determine the exposure time needed to give the required proton do set other arget detectors.Thedosimetryerror associated with each irradiation was taken to be ~20 % based on th e beam uniformity measurements. An E2V Technologies CCD02 device was also irradiat edinthesame way as the CCD47-20devicetoprovidearoughcheckthattheprotonfluxreceive dwasin agreement with previousirradiationstudies.

The CCD was mounted onto the sample plate and rotated into the prot on beam for irradiation, with all CCD pins grounded to avoid static damage. The irradiati on was carried out at room temperature under vacuum. The shielding regime and 10 MeV equivale by the irradiated area of device 9211-4-4 are shown in Figure 6.3. The exposure time for the irradiationwas~10 seconds.

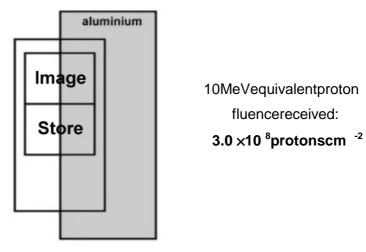


Figure 6.3 A schematic showing the proton irradiated area of device numbe r9211-4-4 and the associated 10 MeV equivalent proton dose received

6.3.1. DarkCurrentChanges

Themeandark current level increased in the areas of each C CDthatwereirradiated. Figure 6.4 showstheaveragepixelamplitudeineachcolumnofthetwoCCDswhi ch scales with the mean energy and the fluence of the protons received by each irradiate d area. The increase in dark currentresulting from the 1.5 ×10 8 and 3.0 ×10 8 10 MeV equivalent proton doses given at the two different accelerator facilities are comparable to wi thin the 20% dosimetry error. The dark current increase in the area of device 9211-5-3, irradiated throug h100 umof copper foil, is far higherduetotheverylargenumberofbrightpixelsgeneratedbyt he2.0MeV protons increasing the average pixel amplitude in these columns. The 'curve' of the l ine in the 2.0 MeV irradiated regionisduetothecopperfoilbeingpositionedataslightlyoffv ertical angle across the device. °C, the unirradiated region in the centre of device 9211-5-3 had a At a temperature of 24 dark current level of ~2600 electrons, while the dark current levels for the 6.5 MeV and 2.0 MeV mean proton energy irradiations were ~3400 electrons and ~14,000 elect rons per pixel 2200to~2900electrons. respectively. The dark currentle velof device 9211-4-4 increased from ~

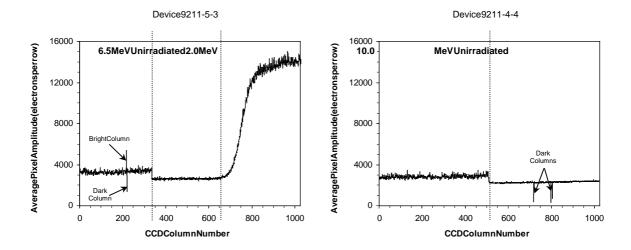


Figure 6.4 Each graph shows the average pixel amplitude of 1000 rows in the image section of the proton-irradiated CCDs

6.4. PreliminaryRTSStudy

AninitialRTSanalysisofdevice9211-4-4wascarriedouttoasse theradiation-inducedRTSpixels. This information was then used as of CCD sequencer and analysis software designed for a more deta. The 600 brightest pixels of the CCD were selected and monitored ever of 12 hours. The CCD was stabilised at a temperature of -10 °Cd pixels studied, 342 were found to exhibit a fluctuating charge level. Figure 1 the irradiated area of the CCD showing the uniform spread of the fluctuating pixels resulting from the irradiation and demonstration proton beam.

ssthegeneralcharacteristics of das abasis for the development iled study of device 9211-5-3. ever y12 seconds over aperiod o'C during data collection. Of the 600 l. Fig ure 6.5 shows a section of the observed bright pixels and ngthe uniformity of the Harwell

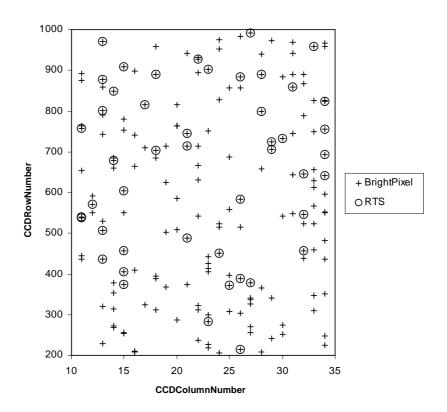


Figure 6.5 The post-irradiation distribution of bright pixels and fluctuating pixels in device 9211-4-4

Anumberofdifferenttypesoffluctuationwereobservedthatcould different categories. For each classification the amplitude of above 5 of the mean pixelle velof a 'Flat' reference bright pixel, the noise distribution was Poissonian in nature. The categories Multi-Stable, Bi-Stable with Wave, and Stable. The characteristics of the control of

beclassified into one of five f the oscillation or transition was where \sigma was 50 electrons, and were called: Wave, Bi-Stable, feachared escribed below:

- Wave: The pixel amplitude varies with a sinusoidal oscillation.
- Bi-Stable:Thepixelshowssharpamplitudetransitionsbetween2distinctl evels.
- Multi-Stable: The pixel shows sharp amplitude transitions between m levels.

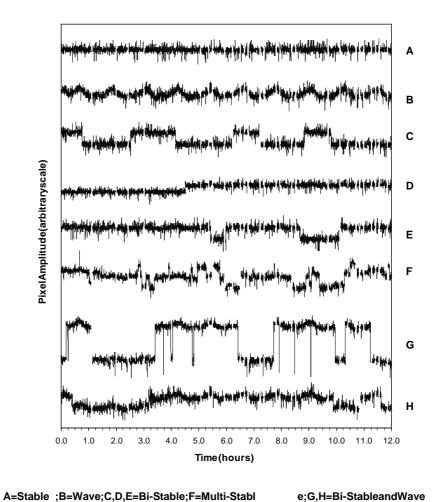
- Bi-Stable with Wave: The pixel shows sharp amplitude transit ions between 2 distinct levels while the amplitude also varies in a sinusoidal fashion.
- Flat:Thepixelshowsnooscillatorynature,ortransitions,that arevisibleabovethepixel noise.

Examples of each fluctuation type are shown in Figure 6.6, spaced out to avoid overlap. Gaps in the data were caused by loss of frame synchronisation for s hort periods during data collection. The number of pixels in each of the five categories is shown in Table 6.2.

Classification	NumberofPixels	%ofTotalPixels
Stable	258	43.0
Wave	71	11.8
Bi-Stable	150	25.0
Multi-Stable	22	3.7
Bi-StablewithWave	99	16.5
Total	600	100

Table 6.2 The number of pixels exhibiting different types of fluctuation, from a total sample of 600 pixels

Thepixelsclassifiedas 'Bi-Stable' pixelsinthisstudyw ereRTSpixelsexhibitingstandardRTS behaviour (Hopkins and Hopkinson 1993), the amplitude of the pixel switching between two distinctlevels. Thehighandlow state time constants were predom in antly of orders ever altens of minutes to hours at the -10 °C monitoring temperature. This is in agreement with previous wor k that investigated the affect of temperature on RTS pixels, s howing that the time constants increase as the temperature is lowered, the time between a mplitude changes becoming many hours and even days when operating at -20 °C (Hopkins and Hopkins on 1995).



A=Stable ;b=vvave;C,D,E=bl-Stable;F=Multi-Stabl e;G,n=bl-Stableandvvave

Figure 6.6 Examples of recorded random telegraph signals from a CCD47-20 opera ting at a temperature of -10 °C

Pixels showing more than two distinct amplitude levels were al so observed and classified as 'Multi-Stable' pixels. Of the RTS pixels generated after protonirradiation, ~3.5% were 'Multi-Stable'. This is comparable to measurements made in previous st udies where the fraction of generated RTS pixels exhibiting multi-stable behaviour after ir radiation with different 10 MeV protondoses was found to be between ~1%-15% (Bond 1996).

The smooth oscillation observed in a number of pixels had a period of a multiple of the oscillation of the many increased proportionally with the mean pixel dark current level and the most of the oscillation of the oscilla

in all pixels with a mean dark current level above \sim 2200 elec trons. The oscillation is not a radiation induced effect, and removing the 'Wave' classification from the collected data reveals that \sim 45% of the monitored pixels had generated RTS character is tics. This is in good agreement with a study involving E2V Technologies CCD02 and Hamamatsu S5466 CCDs irradiated with neutrons (252 Cf), where the fraction of generated bright pixels exhibiting R TS properties was found to be 40% (Stefanov 2001).

6.5. DevelopmentofAnalysisSoftware

The results obtained from the preliminary study indicated that t he RTS pixels were behaving as expected but also indicated ways of improving the method of analysis. Bet tertemperaturecontrol hardware was obtained to remove unwanted oscillations from the data , while a novel CCD sequencer program was developed to remove the synchronisation probl emcausingdatalossand decrease the time between samples to 0.25 seconds. The reduction i n the sample time was to ensure that high frequency transitions were adequately sampled. Anot her practical problem encounteredduringtestingwastheamountoftimerequiredtoobtainlar gedatasetsforstatistical analysis. Previous studies have shown that the time constants o f RTS pixels decrease with increasing temperature (Hopkins and Hopkins on 1993). The same number of switchesfromhigh tolowchargestatecanbeobservedin~1hourat45 °C compared with 12 hours at -10 °C.The data collected from device 9211-5-3 was therefore taken at tempe ratures in the range 45 °C to 55 °C.

The new CCD sequencer code allowed readout of individually sele cted CCD rows in 0.25 second intervals. The resulting images revealed any RTS pixels in the CCD, showing the variation in pixel amplitude over time for each pixel in the selected row of the device. Figure 6.7 shows an example of a recorded CCD image taken at 55 of Cusing the RTS analysis sequencer program.

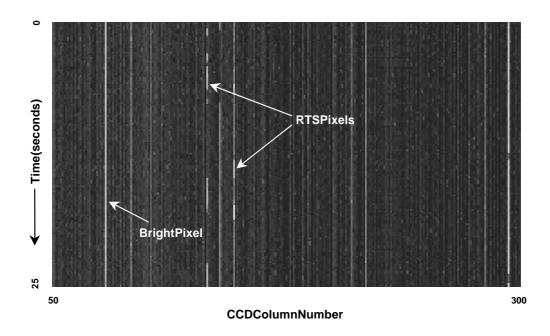


Figure 6.7 An image taken using a sequencer program that only reads out pixels in a selected row of the CCD. Each row in the image is recorded at 0.25 second int ervals revealing the change in amplitude over time of RTS pixels

Each columninthere corded images was then input into RTS analysi the number of distinct amplitude levels present by convolving the with a matched Gaussian and observing the number of peaks and troug convolution. The matched Gaussian was generated by fitting a Gauss amplitude spectrum of 10 'stable' pixels. The raw data and the f shown in Figure 6.8. The analysis software allowed the association o number of distinct amplitudes, giving the mean ADC value of each am between amplitude switches. The four panels of Figure 6.9 illustrate analysis software showing the raw pixel amplitude variation over spectrum, the convolved amplitude spectrum and the gradient of the c used for the figure is that of a 2-level RTS pixel, the two distinct a resolved by the analysis software.

measured amplitudes pectrum
throug hs in the gradient of the
auss ian function to the average
e f itted Gaussian function are
tion o feach CCD pixel with a
plitude level and the time
strate the output from the RTS
overtime, the measured amplitude
fthe convolution. The raw data
istinct amplitude levels being clearly

Thefollowingbulletpointssummarisethestepstakentocharacteris eRTSpixels:

- CCDrowselectedandRTSsequencerusedtoobtainanimageoftheamplitude variation overtimeofallthepixelsintherow
- EachcolumnfromtherecordedimageisreadintotheRTSanalysissoftwa re
- Variationinpixelamplitudeovertimeplotted
- Amplitudespectrumrecordedandplotted
- $\bullet \quad Amplitude spectrum convolved with a matched Gaussian function and plotted$
- Gradientoftheconvolutionplottedandusedtodeterminethenumberofdistinct amplitudelevelspresent
- Timebetweenamplitudeswitchesrecordedforeachdistinctamplit udelevel

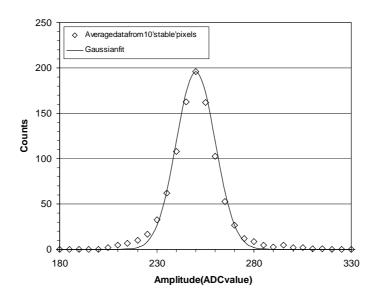


Figure 6.8 The average amplitude spectrum of 10 'stable' CCD pixels fitt ed with a Gaussian function. The fitshown has a σof 10 and was used as the matched Gaussian in the RTS analysis software

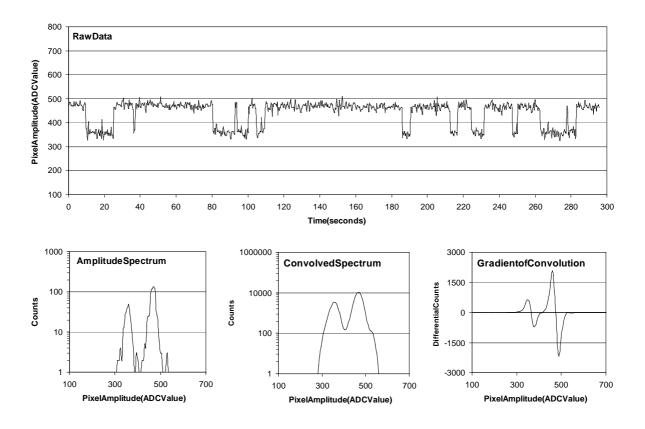


Figure 6.9 Output from the RTS analysis software showing the sensitivity of the software to picking outthe number of distinct amplitude levels present in the awpixel amplitude data. The rawdatawas recorded with the CCD operating at 55 °C

6.6. CharacterisationofRTSPixels

6.6.1. GeneralProperties

×10 8 protons cm ⁻² irradiated region of device 9211-5-3, Fromasample of 1800 pixels in the 3.6 the number of RTS pixels and the number of distinct amplitude level sin each RTS pixel were recorded. The number of amplitude levels was investigated to determine iftheoccurrenceofRTS pixels with more than two amplitude levels scaled with the sta tistical probability of more than oneRTSdefectoccurringinagivenpixel.Ifthemeasurednumberof3or4levelRTS pixelswas thesameasthenumberexpected by the statistical probability, allfluctuatingpixelsshouldbethe result of one or more 2-level transitions within a given pix el. If the observed number of RTS pixelswithmorethantwoamplitudelevelswassignificantlyg reaterthantheexpectednumberit would indicate that RTS pixels with more than two levels are t heresult of additional processes.

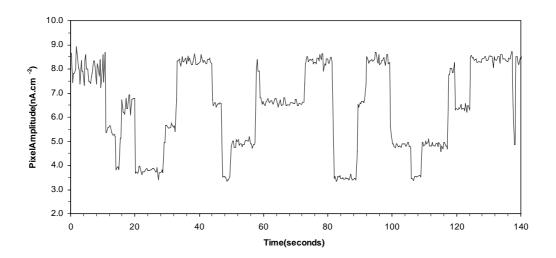
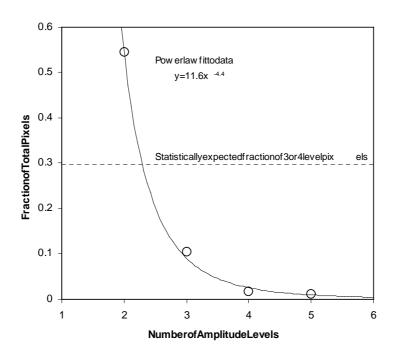


Figure6.10 Amplitudevariationwithtimeofamulti-levelRTSpixelat50 °C

 $An amplitude spectrum was obtained from raw data collected at 50\,$ °CforeachRTSpixelandthe RTS analysis software used for the detection of distinct a mplitudelevels. Figure 6.11 shows the measured distribution of RTS pixels with 2, 3, 4 and 5 amplitude leve ls and the statistically expected fraction that should be present if the explanation for 3level or 4-level RTS pixels is simplythattwo2-levelRTSphenomenaarelocatedwithinthesa mepixel.Theobservednumber icantly below the expected of pixels showing more than two distinct amplitude levels is signif value due to the level of noise in the data reducing the detectionefficiency. Detection thresholds from 5 σ to 10 σ were investigated, all producing data with the same power law fit. No clear evidence that additional processes are responsible for the highe r number of amplitude levels observed was found, the most likely explanation for multi-level R TS being a number of 2-level RTSphenomenaresidinginasinglepixel.



 $\textbf{Figure 6.11} \ The fraction of RTS pixels exhibiting 2, 3, 4 and 5 distinct amplitude levels$

TodeduceiftheRTSphenomenoncouldbelinkedtothehighfieldregi onswithinaCCDpixel, the 'event' sizeofthebrightpixelscontainingRTS was investigated. If a highproportion of RTS pixels were found to be located in single pixel events it would ind icate that the defect causing RTS is located in the inter-electrode or the channel stop high for ield regions, where it is very difficult for charge to diffuse into adjacent pixels. If a large proportion of horizontal or vertical split events were observed, the defect causing RTS may be concentrated in the lower field regions of a pixel, where the charge generated can diffuse into adjacent pixels before being collected into the charge storage region.

Fromatotalof921RTSpixelsobservedinthe 1.5 ×10 8 protonscm -2 irradiated region of device 9211-5-3, only a very small number of the RTS pixels were located adjacent to another bright pixel. Figure 6.12 shows the percentage of the observed RTS pixels h aving different 'event' sizes. The number of 2 pixel events is consistent with the probabi lity of obtaining two single events in adjacent pixels, providing evidence for the location of RTS in the inter-electrode or channels to phigh field regions.

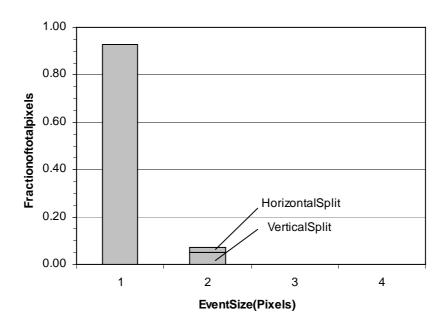


Figure 6.12 The distribution of events izes from a total of 921 RTS pixels

Further evidence for the location of RTS in the high field regions of a pixel can be obtained by considering the physical structure of a pixel and the chargestor age a ndtransport volumes. Figure 6.13 is a diagram of the CCD 47-203-phase pixel structure, indicati ng the charge storage region, the inter-electrode and channel stophigh field regions and the associa tedmovement of charge for the potential situations hown.

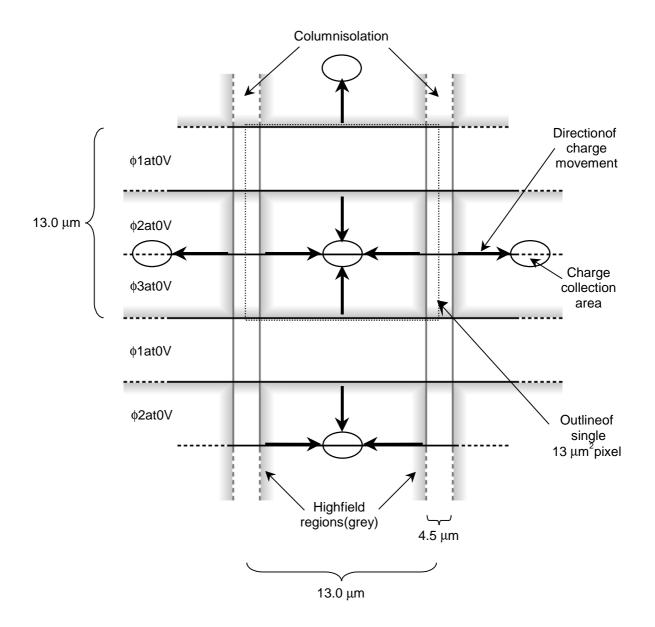


Figure 6.13 The structure of a CCD47-20 pixel indicating the inter-electrod e and channel stop high field regions and the movement of charge into the charge storage regions on of each pixel

Assuming the depth and widthin each case to be the same, the ratio of the volume of the charge storage region in a CCD 47-20 pixel during a single pixel transfer, V_{cs} , to the volume of the high field region within, V_{hf} , can be approximated by:

$$\frac{V_{cs}}{V_{hf}} = \frac{D_{transfer}}{D_{hf}} \tag{6.1}$$

Where $D_{transfer}$ is the distance travelled during a single pixel transfer and D_{hf} is the distance travelledthroughahighfield region during the transfer. Substit uting insuitable values of 13 μ m and 0.2 μ m respectively, V_{cs}/V_{hf} is found to be 65. If this value is comparable to N_{traps}/N_{RTS} , where N_{traps} is the number of traps in a given sample of pixels and N_{RTS} is the number of pixels in the sample showing RTS characteristics, this provides indirect evidence that the RTS phenomenon may be linked with traps located in the high field regions of a CCD pixel.

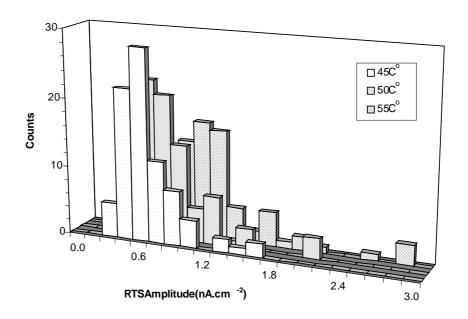
After irradiation of device 9211-4-4 with 3 $\times 10^{-8}$ protons cm $^{-2}$, from an area containing 18400 pixels ~ 1.2% hadachargelevel greater than 5 $\times 10^{-1}$ of the meandark current level. Of this fraction, ~ 45% will exhibit RTS characteristics, i.e. ~ 100 of the sample pixels. An irradiation fluence of 1×10^{-9} protons cm $^{-2}$ results in a CTI of ~ 2 $\times 10^{-4}$ electrons per pixel (Holland et al. 1991). For a MnK α X-ray this CTI value results in the loss of a single elect ron per transfer through 3 pixels. In a sample of 18400 pixels there will therefore be ~ 6000 traps. I n this instance N_{traps}/N_{RTS} is found to be 60, comparable with the V_{cs}/V_{hf} value 65 supporting the high field location of RTS phenomena.

6.6.2. AmplitudeProperties

The mean RTS transition amplitude over a 1 hour period was recorded a t5 °C intervals from 45 °C to 55 °C for 85 RTS pixels. The transition amplitude is the change in dar k current level from the bright pixel pedestal level to the high RTS amplitude.In1hour~80RTStransitionsare observedat45 °C, the number increasing to ~150 at 55 °C.Figure 6.14 shows histograms of the observed amplitudes at 45 °C, 50 °C and 55 °C. As temperature is increased the mean RTS transition amplitude also increases with the distribution of ampli tudes becoming more widely spread. The mean RTS amplitude at each measured temperature is shown in Table 6.3. Figure 6.15 shows an example amplitude versus time plot for an RTS pixelatthethreedifferent temperatures, highlighting the transition amplitude change. The figurealsoshowshowthebright

 $pedestal \, amplitude increases \, with increasing \, temperature \, as \, a \\ the pixel.$

 $result of the {\tt extra} \, dark \, current in$



 $\textbf{Figure 6.14}\ H is tograms of RTS transition amplitudes of 85 RTS pixels at three temperatu$

Temperature(°C)	MeanRTSTransitionAmplitude(nA.cm	
45	0.60	
50	0.75	
55	1.05	

 ${\bf Table 6.3}\ The mean RTS transition amplitude at different temperatures$

res

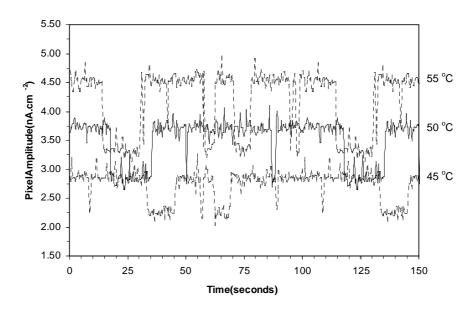


Figure 6.15 The variation intransition amplitude and bright pedestal amplitude with temperature of an RTS pixel

ApreviousinvestigationintoRTSpixelsinaTH7895Mdevice,wi thpixelsof19 um²,lookedto seeiftherewasacorrelationbetweentheRTStransitiona mplitudeandthedarkcurrentpedestal amplitude(Bond1996). No correlation was observed for the data col lectedat 10 °C. Figure 6.16 shows the relationship between RTS transition amplitude and darkcurrentpedestalamplitudefor °Cand55 °CandalsodisplaysthedatarecordedbyBond 24RTSpixelsofdevice9211-5-3at45 at 10 °C (1996). As the temperature increases the spread in the obser ved transition amplitudes becomes larger for higher pedestal amplitudes. A power law trendline can be fitted to all three data sets indicating a power law relationship between the tempe rature of the device and the spreadinthetransitionamplitudeandpedestalamplitudecorrelation.

Themeantransition amplitude of 10RTS pixels was evaluated at 2.5 °Cintervalsfrom45 °Cto 55 °C. Plotting the log e of the transition energy as a function of 1/kT, the RTS tra nsition amplitude was found to follow an Arrhenius relationship with a mean a ctivation energy of $0.53 \pm 0.13 \,\text{eV}$. The results for 10 RTS pixels are shown in Figure 6.17. The e rrors associated with each data point are indicated for one data set and arise from the temperature stability error and the noise variation in the mean amplitude level of a given RTS pixel. This mean activation energy value is comparable with the activation energy of 0.57 $\pm 0.03 \,\mathrm{eV}$ found by Bond (1996) andliesnearthemid-bandenergyof0.55eV,indicatingtheE-centeror theJ-centerasthedefect mostlikelyresponsibleforRTS.

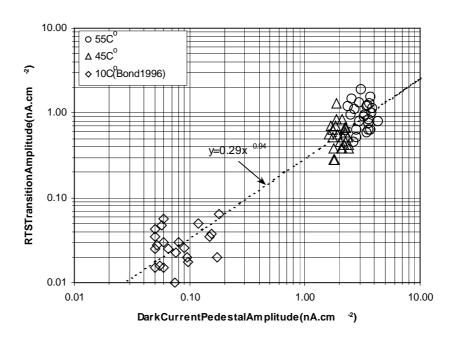


Figure 6.16 RTS transition amplitude variation with dark current pedestal amplitude

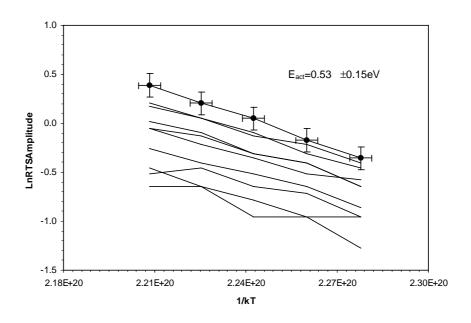


Figure 6.17 RTS transition amplitude activation energy

6.6.3. PeriodProperties

The period of time spent in the high and low amplitude states dur ing each RTS transition was recorded for eight 2-level RTS pixels. A 'switch' from one l evel to another was defined as an amplitudechangeabove 5 of the meandark current pedestalle velof the given pixel, the length of time at a given amplitude level was defined as the 'period'. Data were recorded at 2.5 $^{\circ}C$ intervals from 45 °C to 55 °C. Figure 6.18 shows an example amplitude verses time plot for an RTSpixelatthethreedifferenttemperatureshighlightingt hehighandlowstateperiodchanges. Figure 6.19 shows histograms of the recorded low and high period mea surementsat45 °C,50 °C and 55 °C. The bin size for the low state period histogram is 2 seconds and the bin size for the highstateperiodhistogramis10seconds.

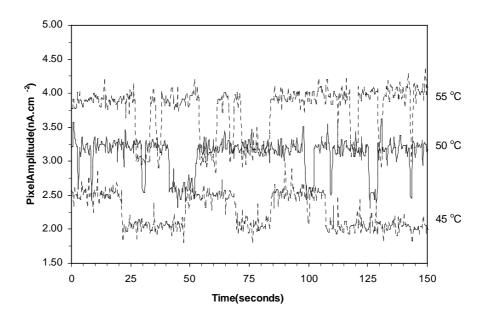


Figure 6.18 The variation in high and low state period with temperature of an RTS pixel

As temperature is increased the distribution of observed high and low state periods becomes narrower, the mean time spent in a high or low state becomings horter. Chi 2 fitting was used to determine the time constant for each state at the five mea sured temperatures. The mean time in the low state was best fit by a single exponential in each ca low state time constant as a function of 1/k Treveals an Arr henius relationship with an activation energy of $0.2 \pm 0.1 \, \text{eV}$.

The high stated at a are better fitted by a combination of two etime constant that varies with temperature in a similar was

xponential functions, revealing one way to that of the low state and a second

timeconstantthatvariesmoremarkedly. Figure 6.20 shows the A rhighstate time constants that have activation energies of 0.1 ± 0.16 shows the low state data. The error associated with each data point period activation energies are within the measured error, indic at in $\sim 0.2 \pm 0.1$ eV is common to all three measured time constants. The RTS found a single time constant for the low state and also only as in state. In each case the period activation energy was found to be the observed value in this study.

rrheniusrelationshipofthetwo $\pm 0.1 \,\mathrm{eV}$ and $0.2 \pm 0.1 \,\mathrm{eV}$ and also pointisshown. All three measured ating that an activation energy of eRTS study by Bond (1996) ngle time constant for the high $0.9 \pm 0.1 \,\mathrm{eV}$, much larger than

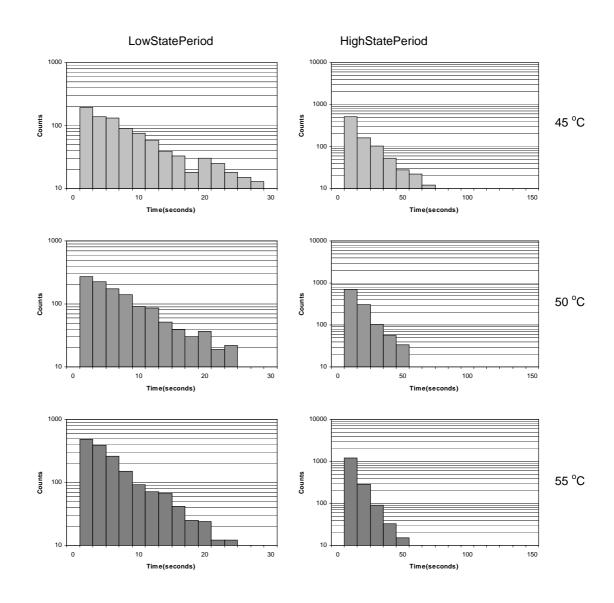


Figure 6.19 Histograms of RTS high and low state periods from a sample of three temperatures 8 RTS pixels at

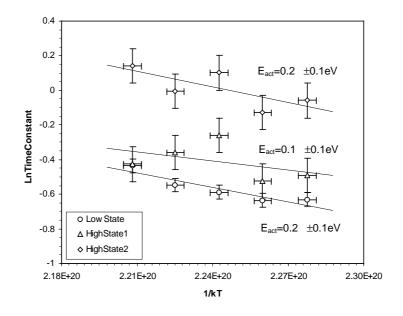


Figure 6.20 RTS high and low state period activation energies

6.6.4. Annealing

The possible link between the RTS phenomenon and the E-centre, sugges ted by the comparable RTS amplitude and E-centre activation energies, was further inverse estigated by an annealing study. Device 9211-5-3 was subjected to an unbiased anneal at a temperature of the E-centre e is ~ 120 °C for a period of 2 hours. The characteristic anneal temperature of the E-centre e is ~ 120 °C. If the mechanism behind the RTS phenomenon is linked to the E-centre, a significant fraction of the RTS pixels observed before heating the devices hould have annealed when investigate dafterward.

 $\label{lem:characterisation} Characterisation of 69RTS pixels, of which 6 had > 2 distinct amplit & ude levels, took place both before and after the anneal. The characterisation involved recor & ding the amplitude of the selected RTS pixels at 0.25 second intervals for 5 minutes. All the sele & cted RTS pixels were from the 3.6×10^8 protonscm $^{-2}$ irradiated area of the CCD. The data was collected at 50 $^{\circ}$ C.$

Post-annealClassification	NumberofPixels	%ofTotalPixels
RTScompletelyannealed	50	72.5
RTSpartiallyannealed	3	4.3
RTSstillpresent	16	23.2
Total	69	100

Table6.4 Post-annealcharacteristicsofasampleof69RTSpixels

Table 6.4 summarises the state of the 69 monitored RTS pixels aft er the anneal. Of the total sample, 28 % of the pixels still showed RTS characteristics, w hile 72 % were completely annealed. This is comparable to the value of ~80% obtained by Holland (1990) when annealing brightpixelsat160 °Cfor16hours.ThelargefractionofRTSpixelsannealedstr onglysupports thecasefortheunderlyingmechanismbehindthephenomenonbeinglinked totheE-centre.Itis than2distinctamplitudelevels,three also interesting to note that of the 6RTS pixels with more annealedcompletelywhile3onlyannealed2oftheiramplitudeleve ls. This observation strongly supports the idea that multi-level RTS is the result of more tha none bi-stable defect occurring within a given pixel, a single RTS defect annealing away reduc ing the number of observed amplitude levels by two in each of the observed cases. Figure 6.21 s hows the variation in amplitude over time for six of the monitored pixels both before and after annel and the contraction of thealing.

Previous work by Bond (1996) observed changes in the amplitude and period o f7 monitored RTS pixels during a stepped anneal study. The study found that RTS de fects are gradually annealed, the time in the high state amplitude became increasingl y long until it eventually became infinite. Incontrast, of the 50 RTS pixels that were annealed in the work carried out for this thesis, 42 displayed amplitudes very close or below the pre-anneal low state amplitude. Of the remaining 8 annealed RTS pixels, only 1 was annealed to an amplitude level comparable to the pre-anneal high state amplitude, the rest annealing to amplitude levels between that of the pre-anneal high and low amplitudes.

There were 16 pixels that still exhibited RTS characterist ics after annealing. In each case the flickering period and transition amplitude had decreased slightly , with the exception of 2 pixels

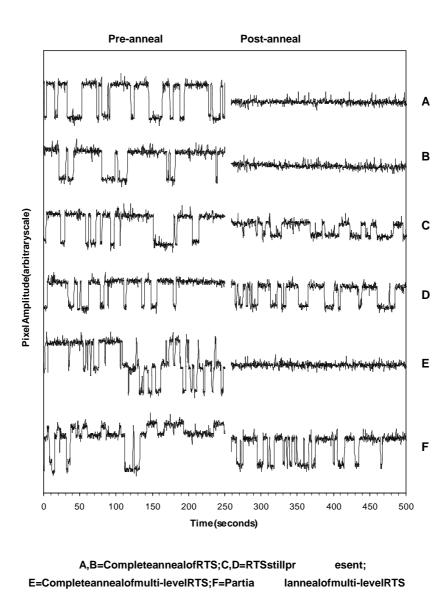


Figure 6.21 The amplitude variation with time of RTS pixels monitored before and after annealing. The amplitude scale is arbitrary to allow the prese ntation of the data, however the relative amplitudes cale of each data set is the same

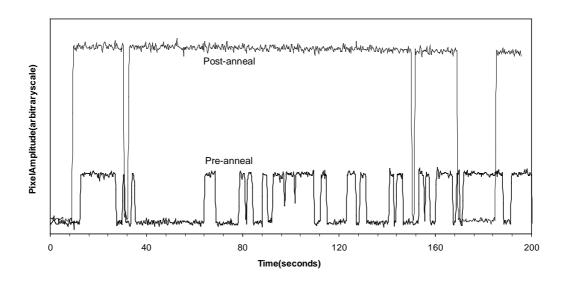


Figure 6.22 The amplitude variation with time of an RTS pixel showing a la rge increase in transitionamplitudeafterannealing

6.7. Discussion

The RTS pixels observed after proton irradiation of CCD47-20 devic es display very sharp amplitudetransitionsbetweendistinctlevelswithhightimecons tantsandwelldefinedactivation $\times 10^{8}$ cm ⁻², approximately 45 % of the energies. After a 10 MeV equivalent proton dose of ~3 bright pixels in the irradiated area show signs of dark curren t fluctuation between two or more distinctamplitudelevelsabove5 ofthemeandarkcurrentlevel. Thespreadofbrightpixels and pixels exhibiting RTS characteristics is uniform throughout the area of irradiation. Of the observed RTS pixels >90 % were isolated events, indicating the mechanism behind the RTS phenomenon may physically lie inside the inter-electrode and channe lstophighfieldregionsofa givenpixel. Consideration of the physical structure and the extent ofthehighfieldregionswithin aCCDpixelalsosupportthishypothesis, the ratio of the charge storagevolumetothevolumeof thehighfieldregioninapixelbeingcomparabletotheratioof thenumberoftrapstothenumber of RTS defects observed within a pixel. These ratios are 65 and 60 respectively.

The number of RTS pixels with >2 distinct amplitude levels is expected number if >2 levels is the result of two or more 2-leve within a given pixel. This is due to the thermal noise on the dark

lower than the statistically 1 RTS mechanisms residing currentlevelmakingithardfor the analysis software to detect the distinct amplitude leve ls. This fact does however support the idea that multi-level RTS is not due to a separate mechanism to that of 2-level RTS, the most likely cause being a number of 2-level RTS being present within the same pixel. The observed partial annealing of multi-level RTS is also in agreement with this hypothesis. RTS pixels exhibiting 3 distinct amplitude levels and not a multiple of 2 c an be explained not only by the inability of the software to detect other amplitude levels a bovethenoiseinthedata, but also by consideration of the magnitude of the high and low state amplitudes of each defect in the pixel. The observed pixel amplitude at any given time is the superposition of the amplitude of each defect in the pixel at that moment. If there are two bi-stabl e defects within a given pixel the resulting pixel amplitude can show 4 amplitude levels or 3. The obse rvation of 3 levels arises when the transition amplitude of each of the bi-stable defects is within the measurement reebi-stabledefects resolution. A similar superposition argument can be used to deduce that forth withinagivenpixel, any number of amplitude levels between 4 and 8 can be observ ed.

The RTS transition amplitude does not show a strong correlation w ith the dark current pedestal amplitude, with transition amplitudes varying over a range of ~1 nA cm ⁻² for a given pedestal amplitude at 45 °C. As temperature is increased the dark current increases, the spread in the observed transition amplitudes becoming larger for higher pedestal amplitudes.

The above observed RTS properties indicate the likely mechanism behind RTS involves discrete transitions between two states separated by an energy barrier . A number of theoretical explanations of the RTS phenomenon have been proposed and the semodels are described below

Field Enhancement: The defect must be field enhanced, accounting for the large tran sition amplitudes, low activation energies and correlation to bright pixels . The defect responsible may be located in the inter-electrode or channel stop regions of a pixel where the electric fieldislargerduetoPoole-Frenkelenhancement.Anothersugges tionisthatchargecaptured by a defect may create an electric field around itself which then influences nearby defects. However, the field created would not reach very far and the re sulting number of defects influencedwouldnotbeenoughtoaccountforthelargetransit ionamplitudesseen. Thisidea is also statistically unlikely if the rearenot many defects presentinthesiliconlattice.

- Multiple Defects: The high transition amplitudes may be the result of many bulk defe cts contributing charge at the same time. Work has shown that arou nd 50 defects would be required to act together to generate the amplitudes seen and so t his theory is thought to be unlikely (Kirtonetal. 1989).
- Multi-stable Defect: The observed well defined time constants suggest that a multistable r, may be responsible for the defect, with two or more states separated by an energy barrie RTS phenomenon. The defect must be common a sit is widely seen a fter.andinsomecases n defects with the before, proton irradiation of a device. There are however, no know appropriate activation energy and energy states. Normally the time constants of capture and emission of charge are thermally independent. This is not tr ue for the observed RTS time constants, which show a strong temperature dependence. The RTS swit ching phenomenon therefore involves a mechanism that is independent of simple e lectron capture and emission probabilities.

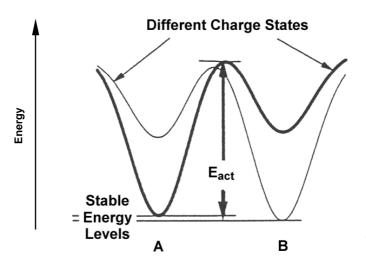


Figure 6.23 Energyverses defect configuration for a defect with two stables ta tes, A and B

A proposed model is a multi-stable defect with the stable conf iguration dependent on the charge state: state A being stable for one charge state, and state B being stable for another

(Chantre 1989, Watkins 1991). The configuration can be flipped over the pot ential barrier fromstateAtostateBbythermalfluctuations.Theenergylevelofe achstate, along with any fieldenhancement, will determine the level of thermally gene ratedconductionbandelectrons and therefore the dark current amplitude level. If one state is nearer the mid gap than the othertherewillbetwocleardarkcurrentlevelsobservedafterfi eldenhancement.Thismodel can not explain the multi-level RTS pixels observed, if they a re the result of a different process to 2-level RTS, and also does not account for the second hi gh period time constant observedinthedata. Figure 6.23 illustrates the proposed defect. I nonecharge state, state A hasthelowerenergy, while in the other charge state, state Bhasthelow erenergy.

ReorientationoftheE-centre: This model was suggested by Bond (1996) and involves the reorientation of the E-centre in a strong electric field. The correlation between RTS behaviour and dark current spikes indicates that the defect re sponsible for the dark current spikes may also be the cause of RTS. The E-centre is a common bul k defect in proton irradiated silicon and is generated in numbers large enough to expl ain the large fraction of pixels exhibiting RTS after irradiation. It has been shown that t he E-centre in its neutral charge state has an extra positive charge on the P-atom, and a corresponding extra electron orbital (Watkins and Corbett 1964). The defect has a resulting di polemoment, and the field enhancement factor caused by the defect will depend on its orient ation within the applied electric field (Martin et al. 1981). The E-centre has been obs erved to reorient its axis, the vacancy taking the place of any one of the four nearest silicon atoms to the phosphorous atom, moving through the silicon lattice by thermally overcoming pot entialbarriers(Watkins and Corbett 1964). Figure 6.24 shows the structure of the silicon latti ce containing an E-centre defect and one possible reorientation. The level of da rk current generation is dependent on the orientation of the defect within the applied ele ctric field. A movement of thevacancyfromasmallangletoalargeanglerelative totheelectricfieldvectorwillresult inlargeamplitudeRTSsignalsandvice-versa.

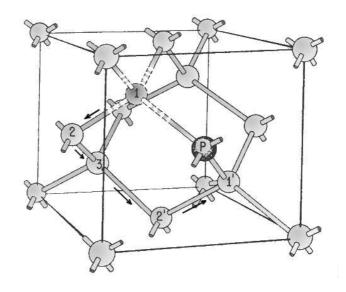


Figure 6.24 The silicon lattice containing an E-centre defect. The vacanc y can reorient itself from its normal position nearest the phosphorous atom to a new nearest site by moving through the lattice as shown

For this model to be viable, RTS time constants should be corre lated to the kinetics of reorientation of the defect. The measured activation energies for reorientation are 0.93 ± 0.05 eV, higher than the observed 0.2 ± 0.1 eV observed in the CCD47-20 study presented. The model also explains the lack of a correlation betwe enRTS amplitude and the dark current pedestal, and lack of any direct evidence for fie ld enhancement, as the model assumes the amplitude is dependent on the defect orientation, not the electric field strength. Electric fields have however been observed to influence thereor ientation kinetics of defects, whichmayexplainthelargevariationintimeconstantsobserved(Kimerl ing1979).

The models described above each provide explanations for a number of ob served RTS characteristics, but not all. The reorientation of the E-centr e provides the most detailed description of a mechanism to explain the RTS phenomenon, but does not a count for the two high state time constants observed in the data obtained for this thesis. The work in this chapter

has shown that the most likely model for RTS involves the E-ce ntre, the high field regions of a device and a single bi-stable mechanism.

6.8. Summary

This chapter has presented an in-depth study of fluctuating pixels inprotonirradiatedCCDs.The prevalence of the `Random Telegraph Signal' phenomenon and the lackofunderstandingofthe underlying mechanism was described first, followed by descriptio ns of the devices used for the study. The irradiation methodology was then presented followed by an i n-depth analysis of the induced RTS pixel characteristics. The RTS phenomenon was shown to be strongly linked with the E-centre and most likely physically located within the hig h field regions of a device. A number of models for the underlying mechanism have been presented, the most plausible involving a single bi-stable defect configuration that can be the rmally flipped from one stable statetoanothergivingrisetotheamplitudeandperiodcharacterist icsobserved.

Chapter7:ConclusionsandFutureWork

This chapter summarises the main conclusions of the three studies carried out for this thesis and indicates directions for possible future work in each case.

7.1. L3VisionRadiationTesting

To assess the potential of using L3Vision technology in space appl ications, two E2V TechnologiesCCD65devicesincorporatingtheL3Visiontechnology were irradiated with proton fluences representative of total mission fluences received by spacecraft operating in low Earth orbit. The main conclusions of the study are given below:

- Afterirradiationthetwodeviceswereshowntooperateasexpectedwitht increaseindarkcurrentandnumberofbrightpixelsgeneratedbyeachirradia tionbeing comparabletopreviousprotonirradiationstudiesonotherdevices.
- TheL3Visiongainregisteroperatednormallyafterprotonirradiation
- Brightpixelsgeneratedinthegainregisterappearednottobelocatedinth ehighfield avalancheregionsastheyexhibitedsimilarcharacteristicstot hebrightpixelsgenerated intheimagesectionofthedevice.

The study has revealed no significant problems inhibiting the use of L3Vision technology in spaceapplicationsalthoughthereisaneedforfurtherprotonirradiations tudiesinvolvingalarger number of devices to improve on current statistics and deduce if a bright defect generated in the avalanche region of a pixel in the gain register can cause device failure. A proton irradiation study of a batch of ~25 CCD65 devices featuring the L3Vision techno logy is currently being planned to address this question.

7.2. TheEffectofLowEnergyProtonsonCCDs

The impact of low energy protons on the operational characterist ics of CCD22 devices was investigated to assess the damage contribution of low energy prot ons to the observed on-orbit CTEdegradationoftheEPICMOSdevicesofXMM-Newton.Themainconc lusionsofthestudy are:

- ProtonswithenergyoforderafewkeVcausemoredamagethanthatexpecte dbythe
 Non-IonisingEnergyLossfunctionastheydepositthemajorityoftheirenergy the CCD.
- Thegreatestamountofdamagetotheburiedchannelisassociatedwiththe highest amountofenergydepositedwithinit,themostdamagecausedbyprotonsof~220keV whichcometorestwithintheCCDburiedchannelyolume.
- The component of the observed CTE degradation of the EPICMOS devices of XMM-Newton attributed to soft protons is small, <20%.
- TheoperationoftheXMM-Newtonspacecraftisoptimalforkeepingthesof tprotonflux reachingtheEPICMOSCCDstoaminimum.

The study also resulted in the development of a computational model that can be used to simulate the CTI expected afterir radiation of a CCD with low energy protons. In put to the model involves specifying a representative CCD structure, in this case a CCD 22 device, and can therefore be used to model other CCD devices in the future.

7.3. RandomTelegraphSignals

A detailed investigation of the 'Random Telegraph Signal' phenomenon has been carried out withanumber of new findings being made. The study involved their radiation of two CCD 47-20 devices with protons, and the subsequent development of detailed analy sissoftware to allow the characterisation of radiation induced RTS pixels. The main finding softhe RTS investigation are as follows:

- Approximately45% of bright pixels generated afterprotonir radiation exhibit R TS behaviour.
- TheobservedRTSpixelsexhibitedamplitudeandperiodbehaviourcomparableto previousstudies.

- OccurrencestatisticsandannealingresultsshowthemechanismforRTSi nvolvestwo distinctamplitudelevels,RTSpixelswith>2amplitudelevelsbeingthe resultofmore thanonesuchbi-stabledefectresidingwithinthepixel.
- Thelargeamplitudevariations associated with RTS pixels indicate the RTS phenomenon is linked with the high field regions of a CCD pixel. Consideration of the pixe the chargestorage volume and extent of the high field region within a pixel als this finding.
- ThelargenumberofRTSpixelsgeneratedafterirradiationandthelarge amountofRTS pixelsannealedat120 °Cprovidesstrongevidencethattheunderlyingmechanism behindRTSislinkedwiththeE-centre.TheRTSamplitudeactivationen ergywasfound tobearoundmid-band,0.53 ±0.13eV,alsosupportingthelinkwiththeE-centrewhich liesat0.44eVbelowtheconductionband.

Future work will involve the use of a proton microprobeto 'inje of a CCD pixel allowing direct measurement of the location of bri volume of a pixel and a ccurate correlation with the high field a 2003).

ct' protons into specific regions ght and RTS defects within the ndchargestor ageregions (Simon

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